

# Fundamentals of CMOS Design I

Ronald Valenzuela - [ronaldv@synopsys.com](mailto:ronaldv@synopsys.com)  
Corporate Application Engineer at Synopsys



# Outline

Motivation

Transistors

Digital Circuits



# Motivation

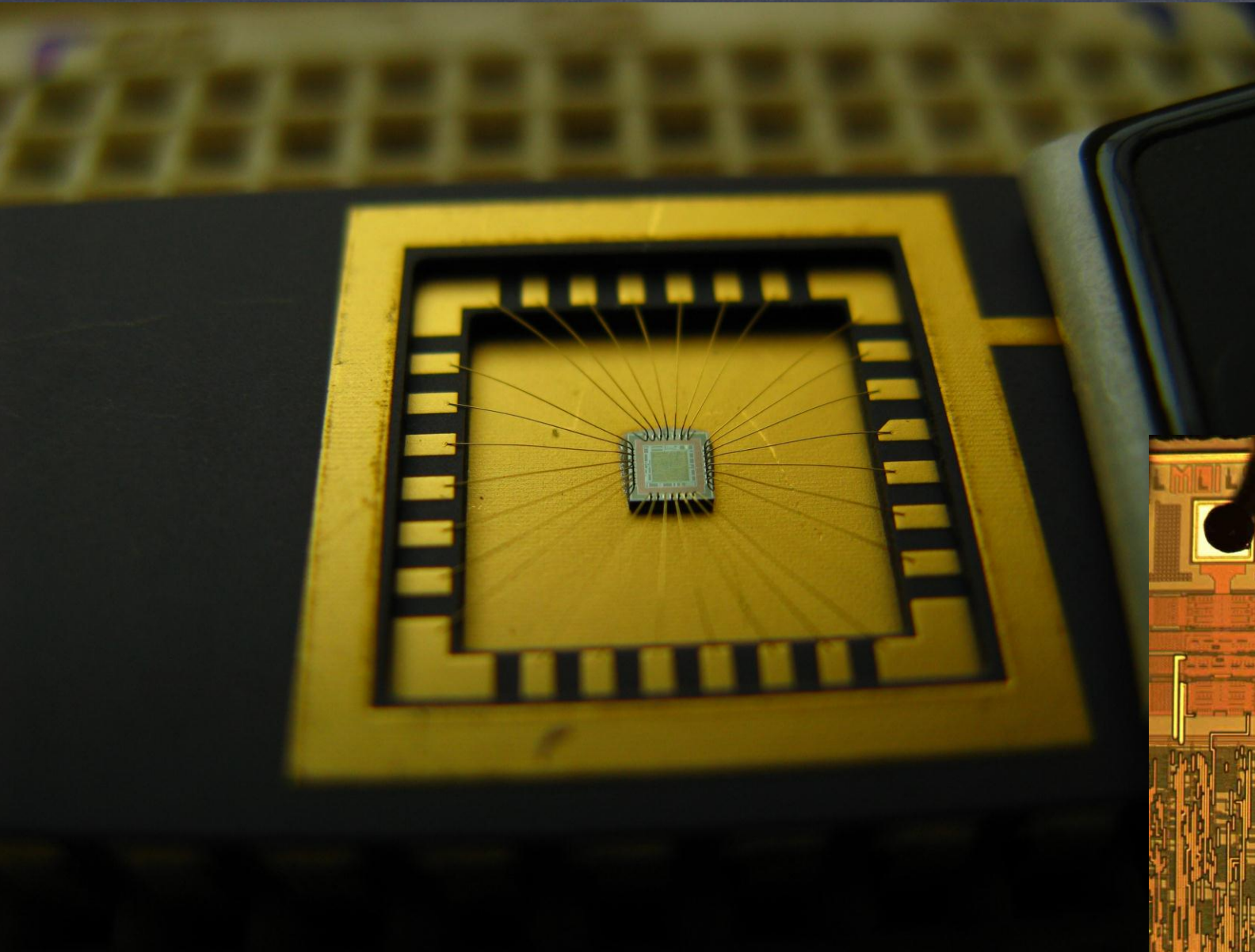


# Challenge - Why VLSI?

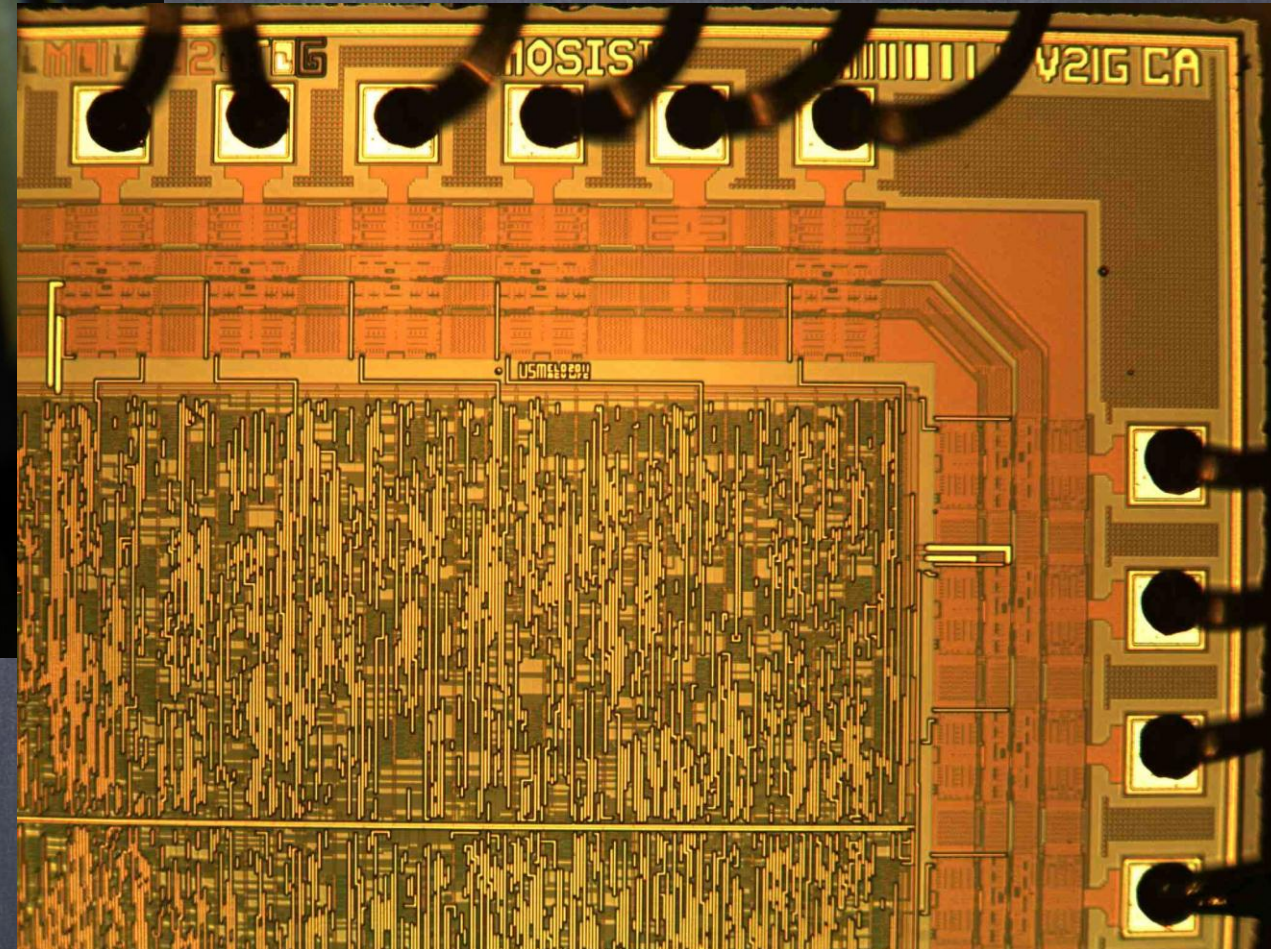
- No other technology can do so much at so low cost and using such few energy.
- Easier to move electrons than things. Check a mechanic counter part below.
- And of course... because we CAN and is FUN!!

( <http://www.computerhistory.org/babbage/overview/> )





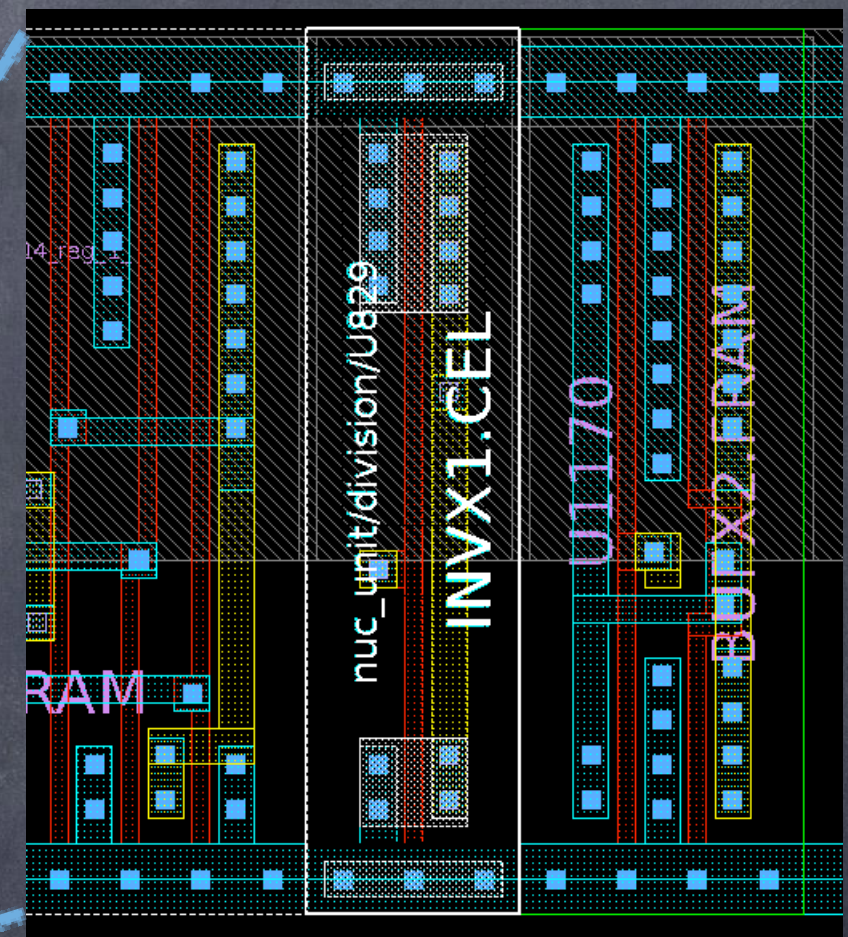
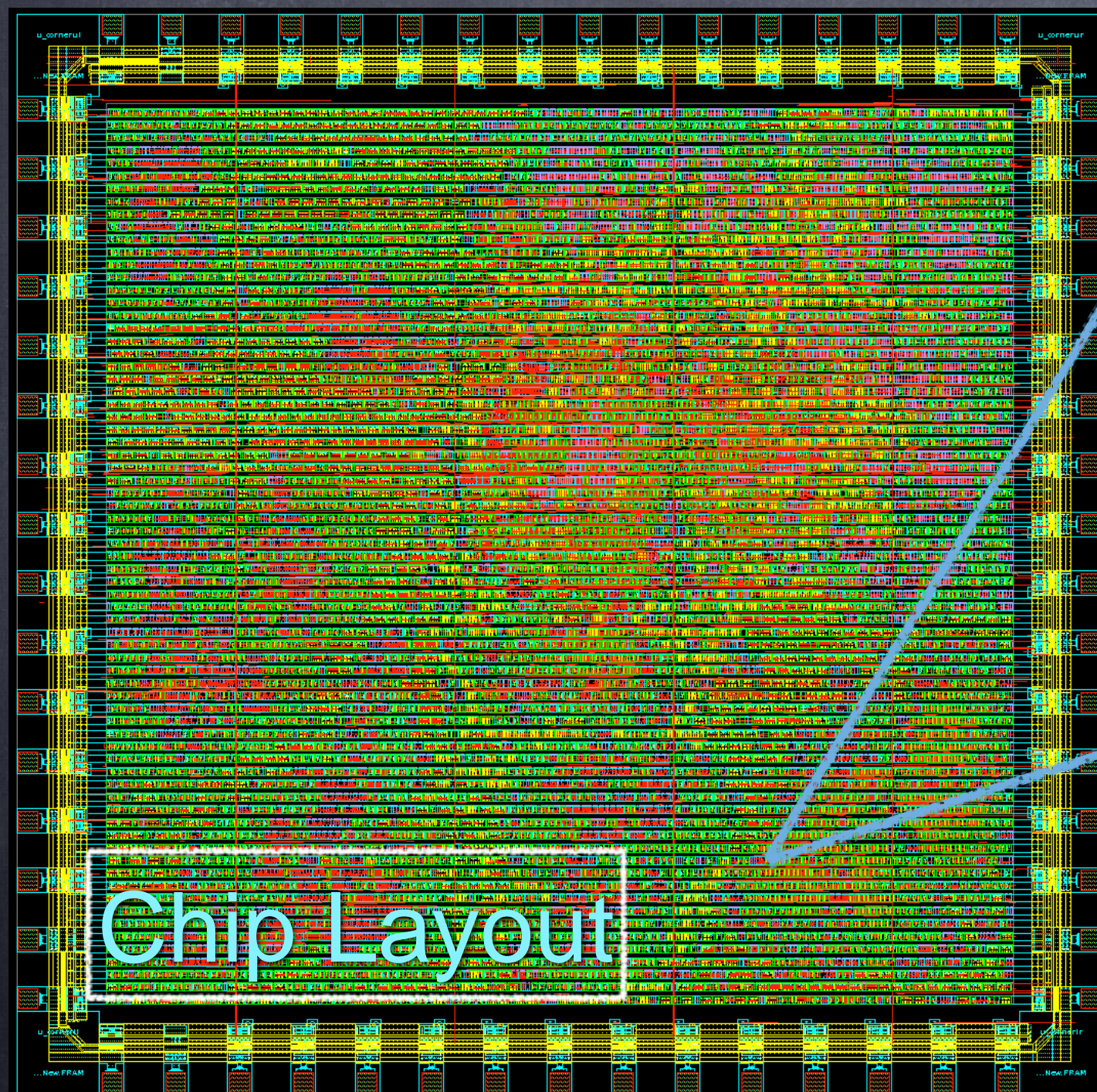
\*Courtesy of UTSFM



A Chip designed in Chile!  
(Fabricated for free through MOSIS)



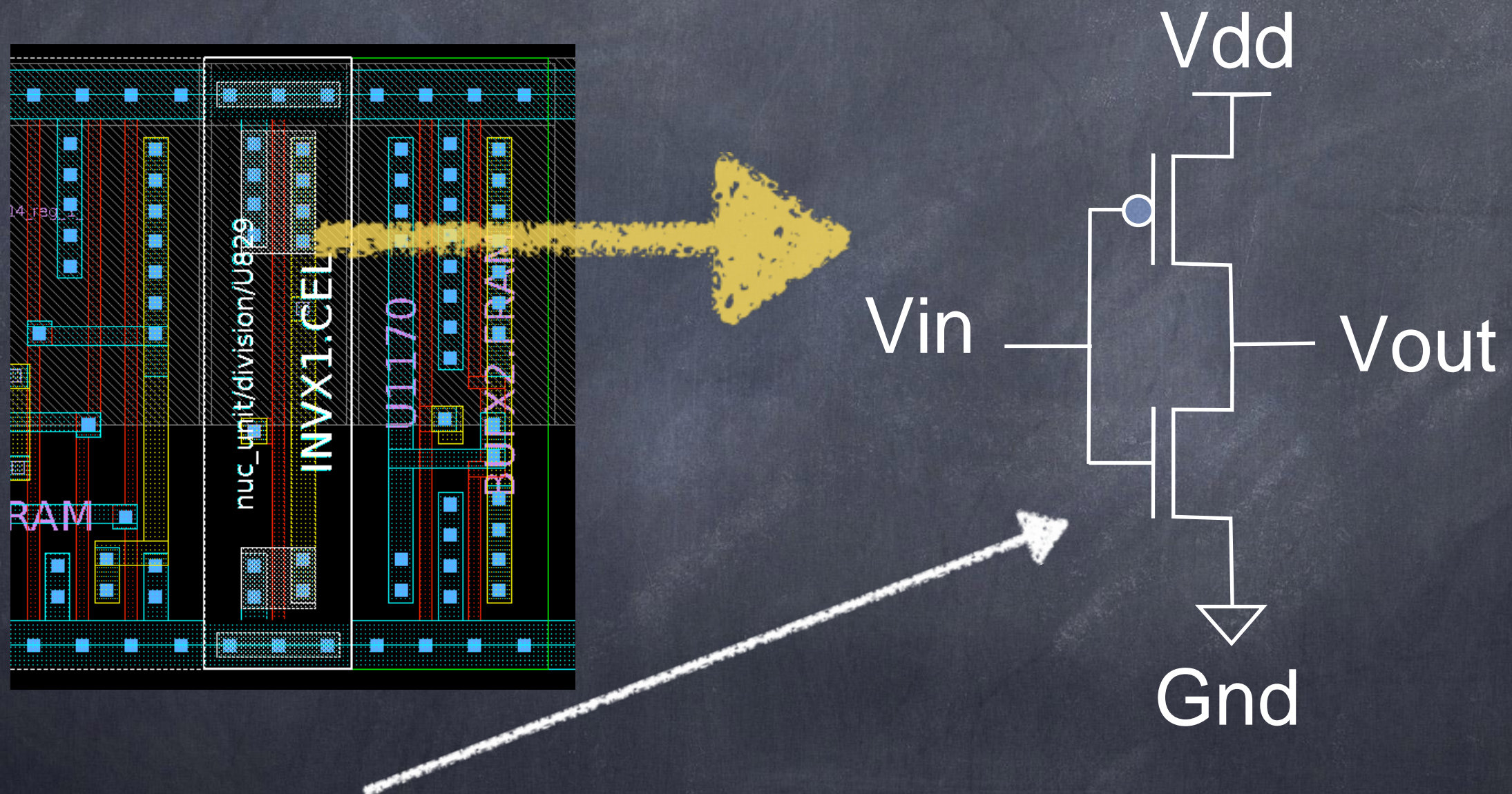
# But how to get there? Let's look inside!



Zoom x1000



Rectangles that will be used to engrave circuits through lithography



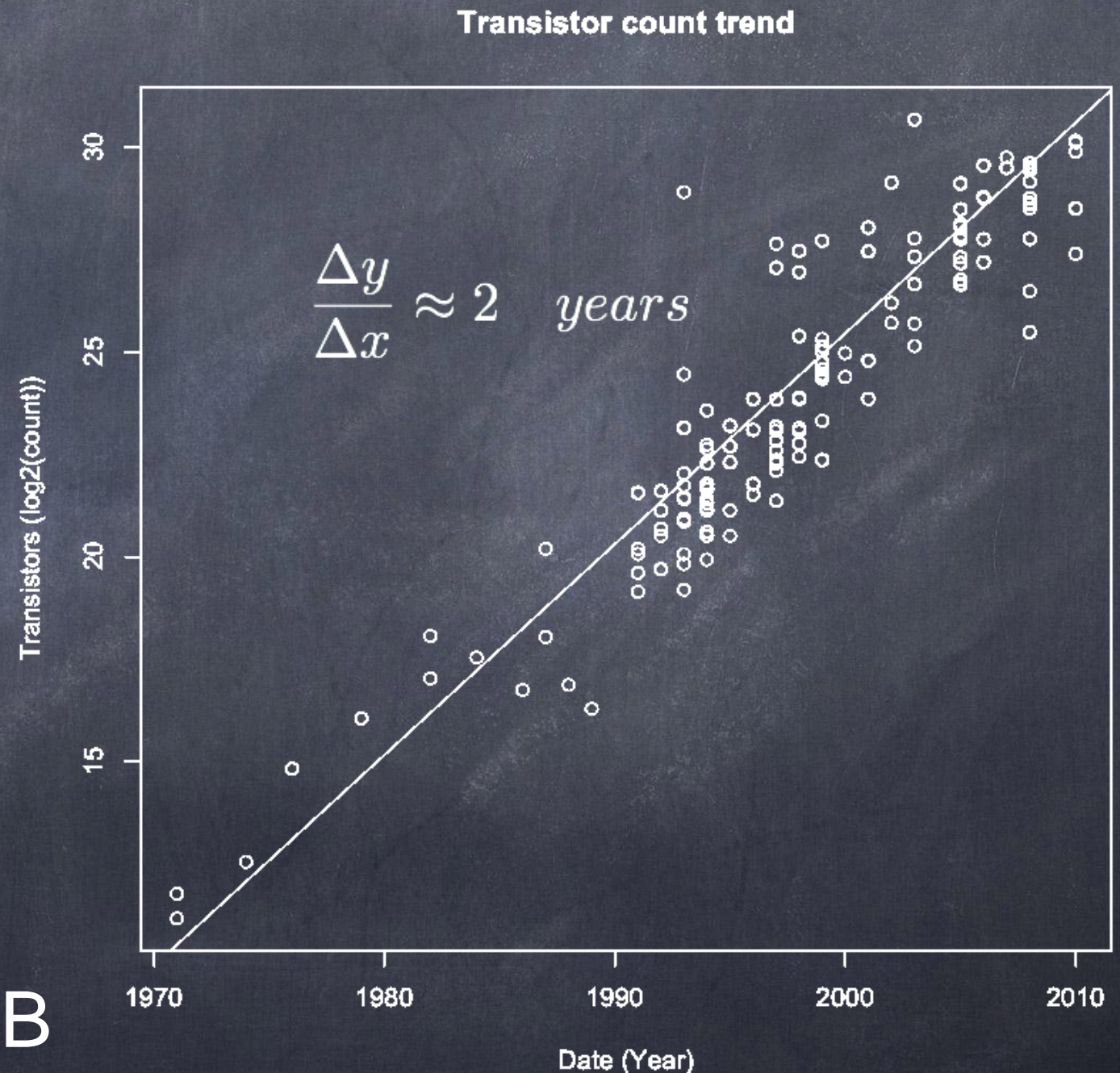
At the bottom what we have are TRANSISTORS



# Moore

"Cramming more components onto integrated circuits",  
Electronics Magazine, Aprils 19th, 1965

- Much smaller
- More transistors
- More features
- Much Cheaper
- More data?
- ITRS
- Stanford CPUDB





# Scaling - Dennard

- Moore's article was about promoting a new technology. On the other side Robert Dennard (IBM) relates parameter scaling on a transistor with its features.

	Feature	Factor
• V scales $\rightarrow V/a$	More Transistors	$a^2$
• L scales $\rightarrow L/a$	Faster, delay	$1/a$
• C scales $\rightarrow C/a$	Less energy	$1/a^2$

“Design of Ion-Implanted MOSFET's with Very Small Physical Dimensions”, IEEE JOURNAL OF SOLID-STATE CIRCUITS, vol. SC-9, no. 5, pp. 256–268, October 1974.



# Some difficulties

- Complexity
  - Verification
- Power
  - Heat
  - Supply
- Noise
  - Signal integrity, coupling
- Process Variation, Robustness, Reliability
  - Fabricate 1B transistors/chip and most chances are that some have defects
  - Soft errors, timing errors, defects, variations
- Non recurring engineering costs (NRE)
  - Design time, CAD tools
  - Mask costs (tooling needed to create IC)
  - NRE fabrication charges (fabs are VERY expensive)



**My name's Guybrush Threepwood, and I want to be a pirate!**

OK... motivated already?



# Transistors

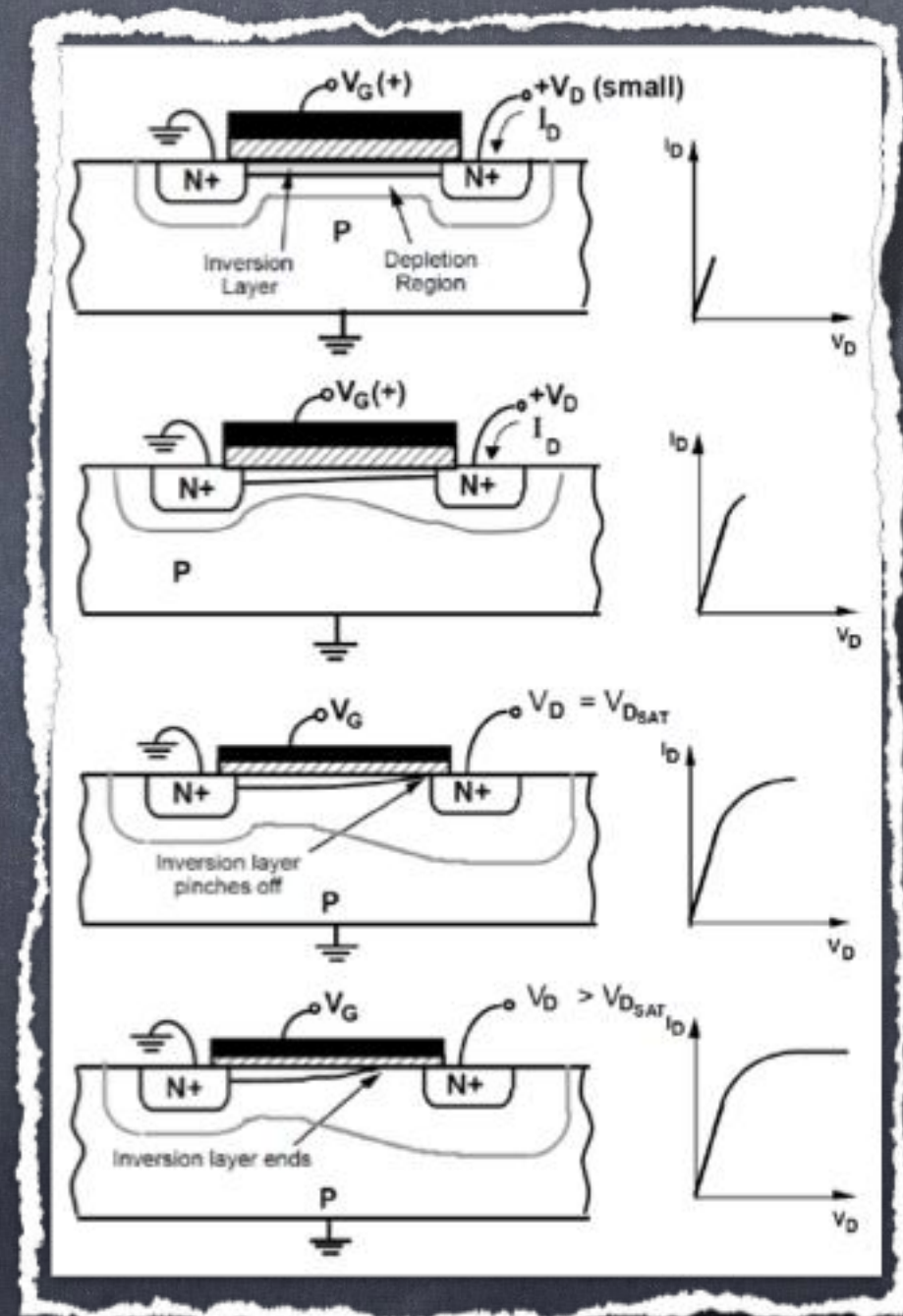


# Transistor is a **MONSTER**

A non-linear monster in fact



\* From Prof. James Harris Notes (Stanford)

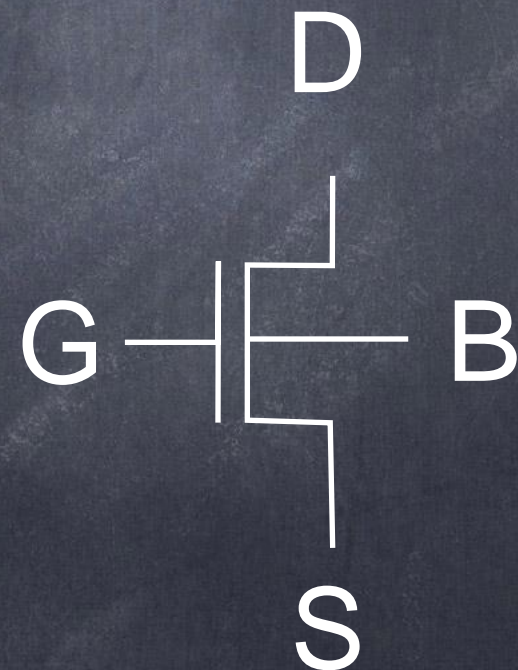
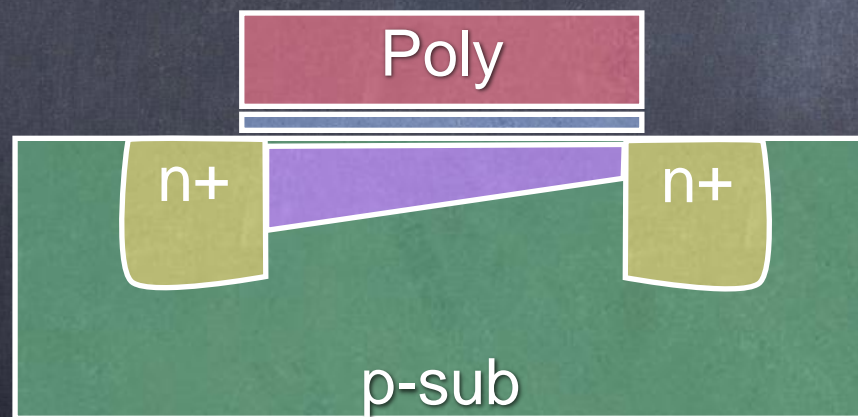




# Transistor

- MOSFET

- Controlled by 4 voltages:  $V_g$ ,  $V_d$ ,  $V_s$ ,  $V_b$ .
- Also by  $V_t$ , threshold voltage (set during fabrication)



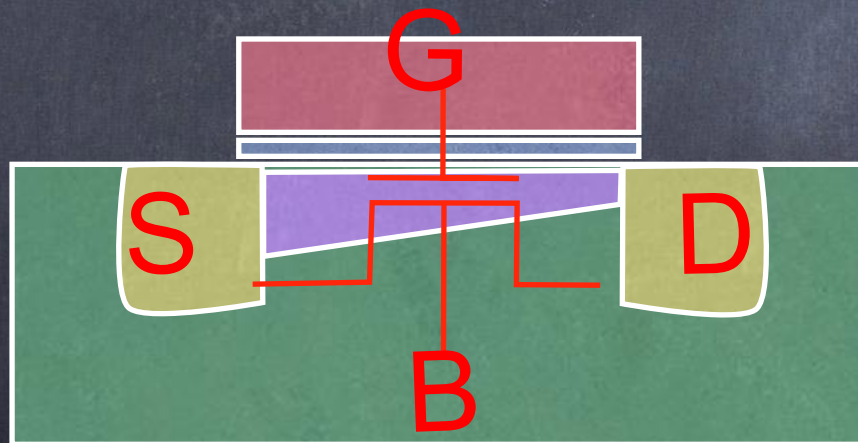
Highly non linear models, must be abstracted to handle billion transistor designs.



# Transistor

- MOSFET

- Controlled by 4 voltages:  $V_g$ ,  $V_d$ ,  $V_s$ ,  $V_b$ .
- Also by  $V_t$ , threshold voltage (set during fabrication)

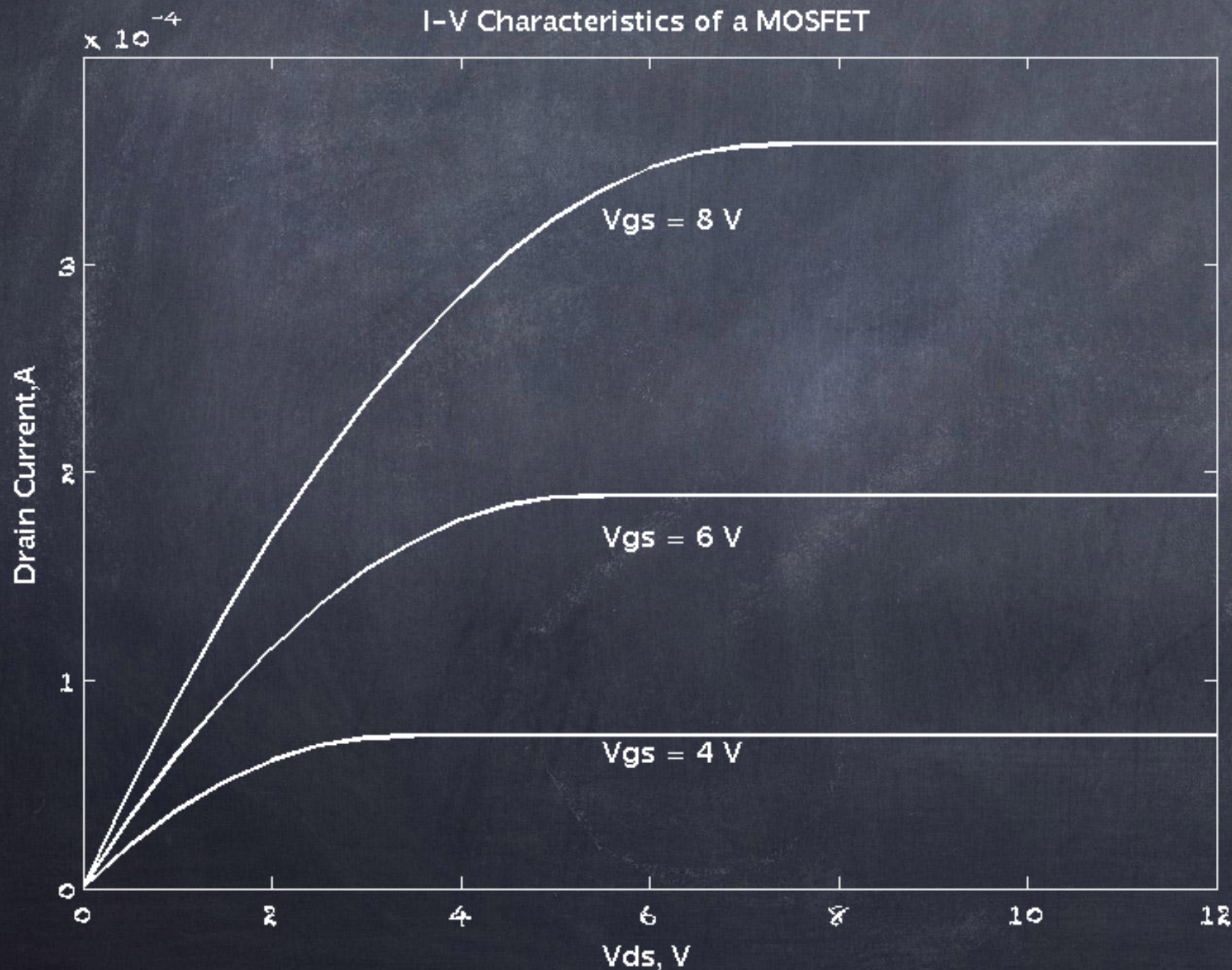


Highly non linear models, must be abstracted to handle billion transistor designs.



# Transistor

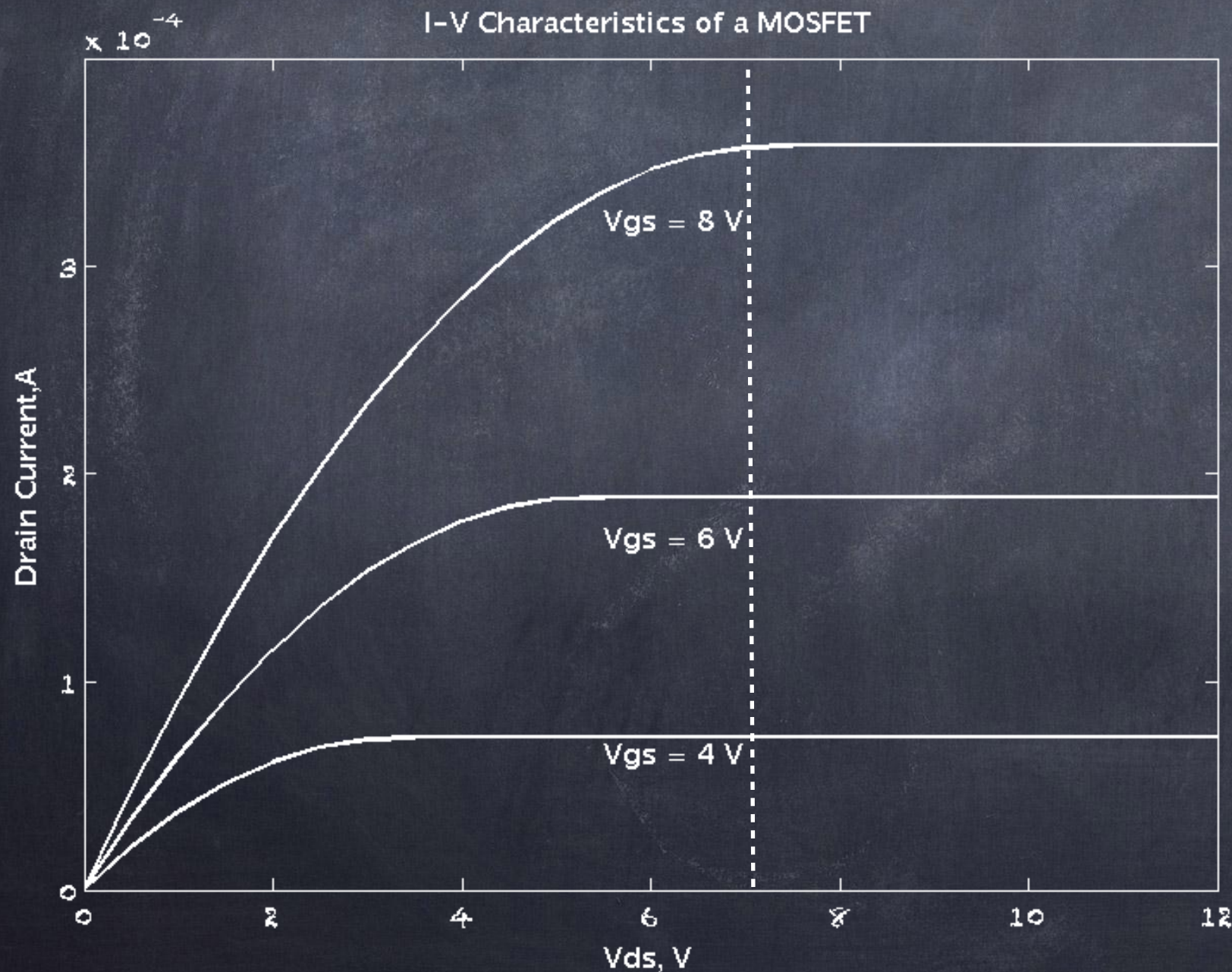
- Often characterized by its current to voltage curve.





# Transistor

- Often characterized by its current to voltage curve.



## 3 Operating zones

$I_{ds} = 0$

Cutoff:  $V_{gs} < V_t$

$I_{ds} = \mu C_{ox} W/L (V_{ov} - V_{ds}/2) V_{ds}$

Linear:  $V_{gs} - V_t > V_{ds}$

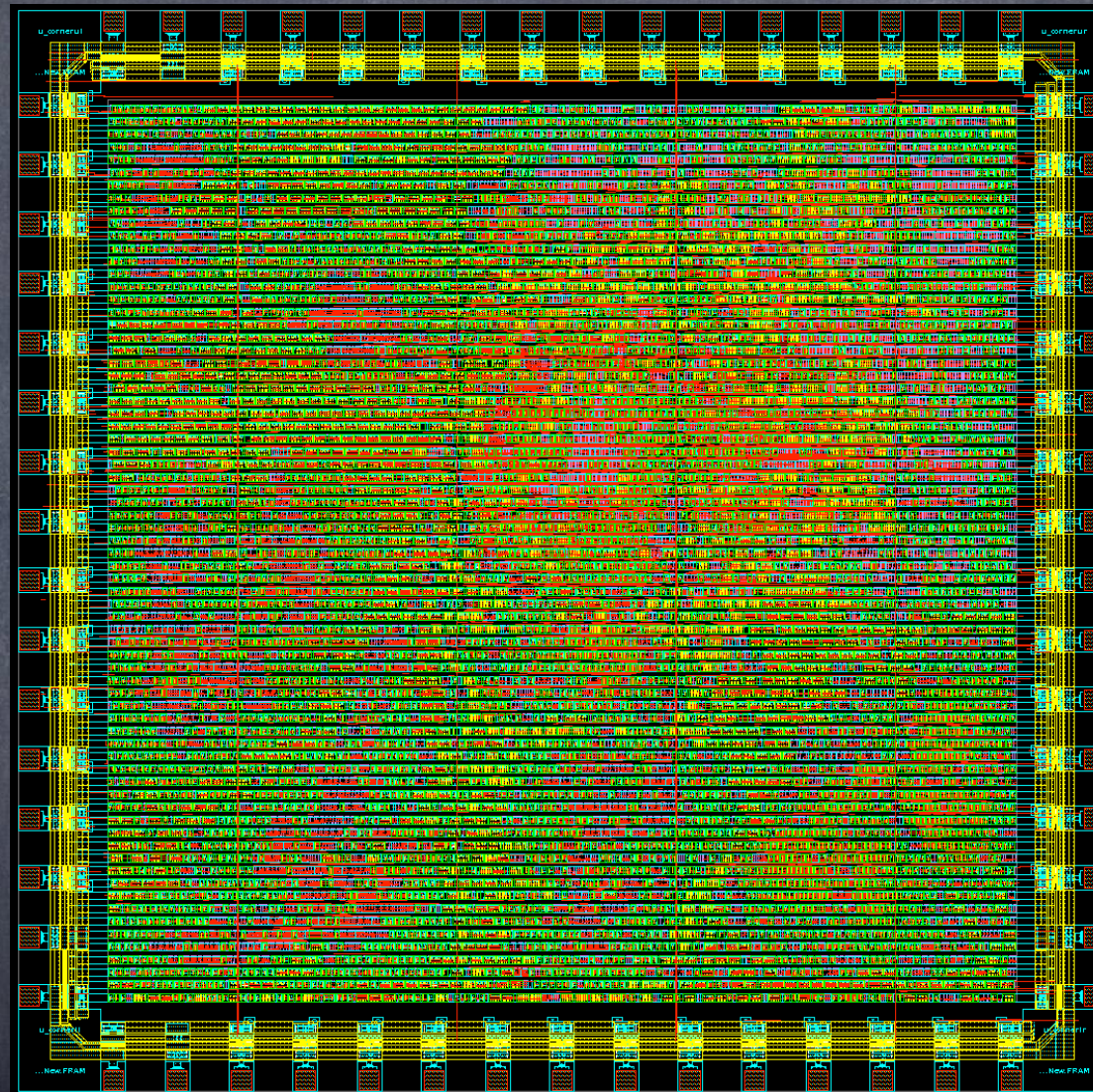
$I_{ds} = 1/2 \mu C_{ox} W/L (V_{ov})^2$

Saturation:  $V_{gs} - V_t < V_{ds}$

\* $V_{ov} = V_{gs} - V_t$



# Transistors



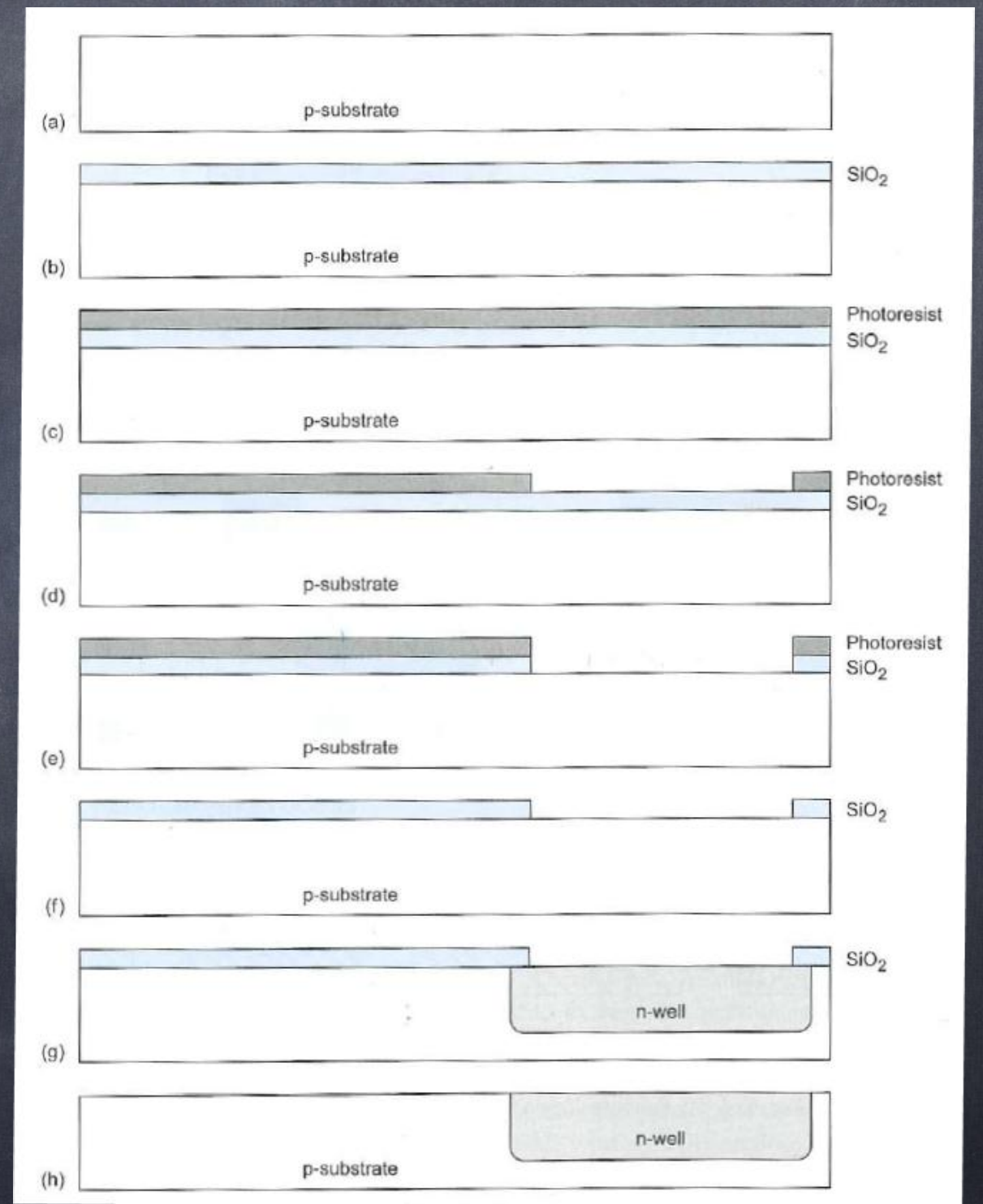
We Need SIMPLER models to handle Billion Transistor Design (More on this later)



# Yeah sure, but where can I get one?

You print, they build

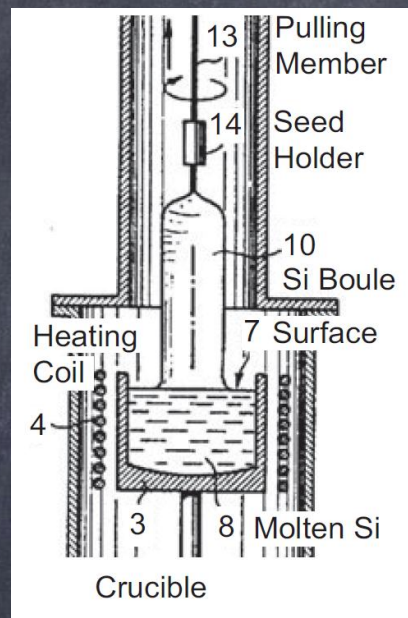
The picture shows how an n-type well is created over a p-type silicon wafer.



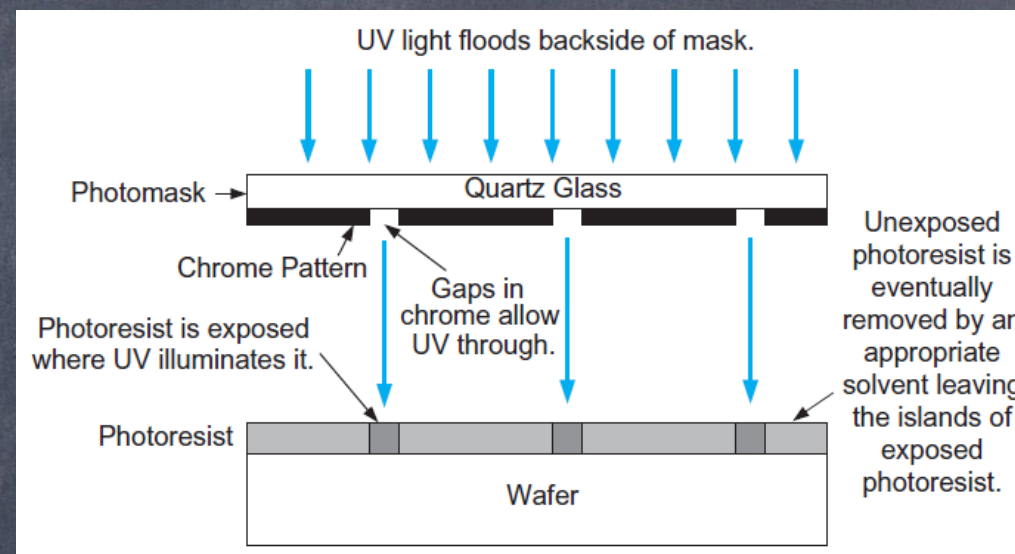
*\*Weste, Harris - CMOS VLSI Design 4th Edition*



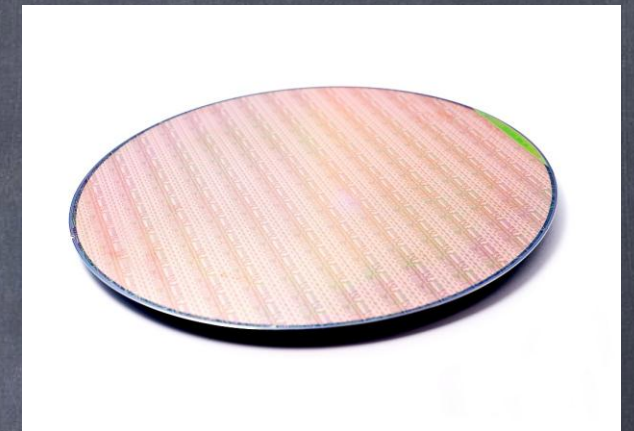
# Circuits are printed in Wafers



Raw Wafer  
(ie: 100 P-type Si  
Wafer)



Photolithography

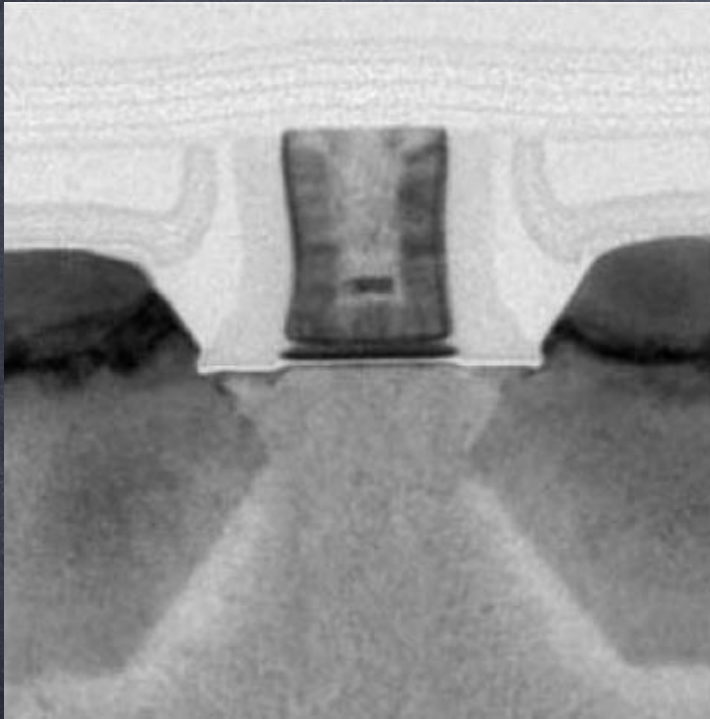


Wafer

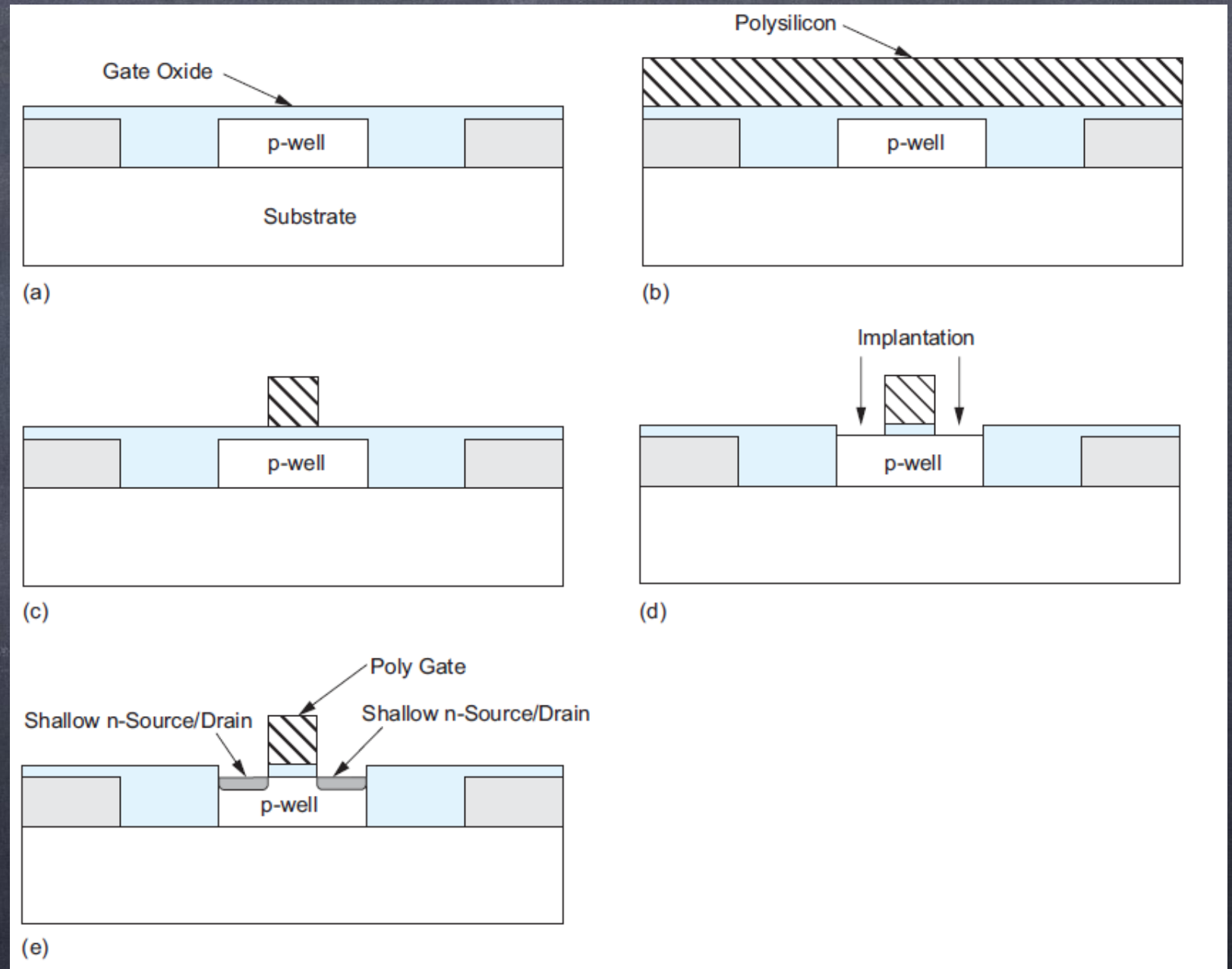
Process



# Quick look at fabrication



The Monster





# Digital Circuits

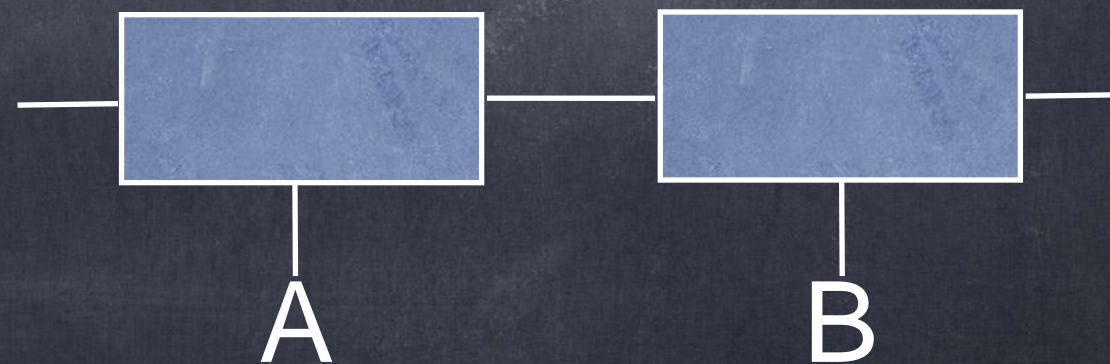
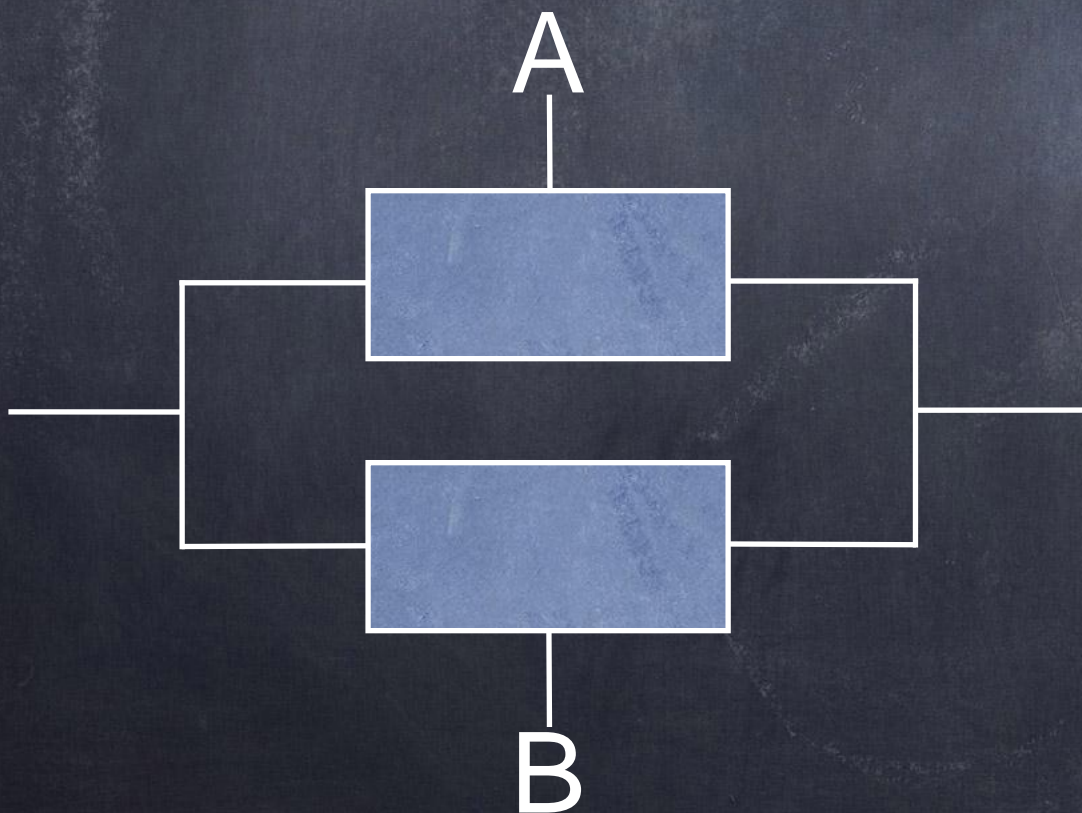
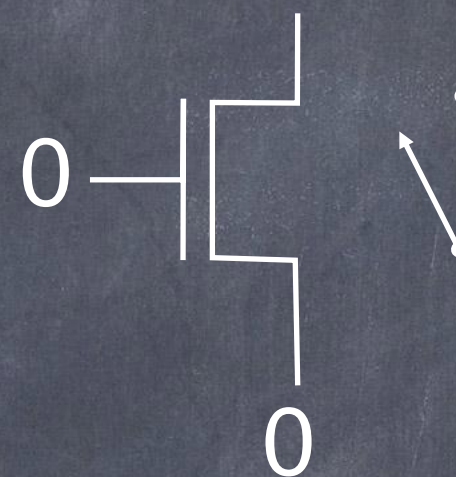
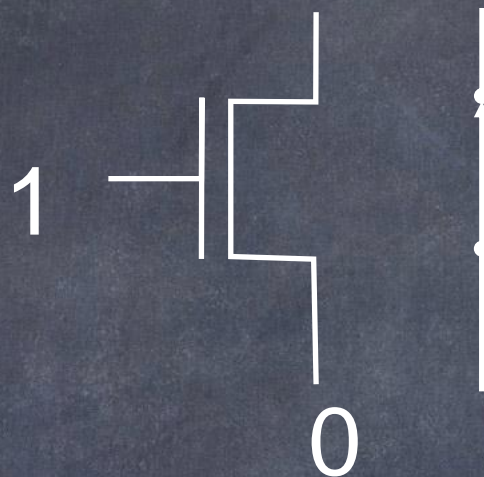


# Digital Circuits

- Good CMOS gates are:
  - Uni-directional
  - Rail to rail
  - Noise attenuated
  - Defined by binary equations
  - Low dynamic power dissipation



# Switch Networks

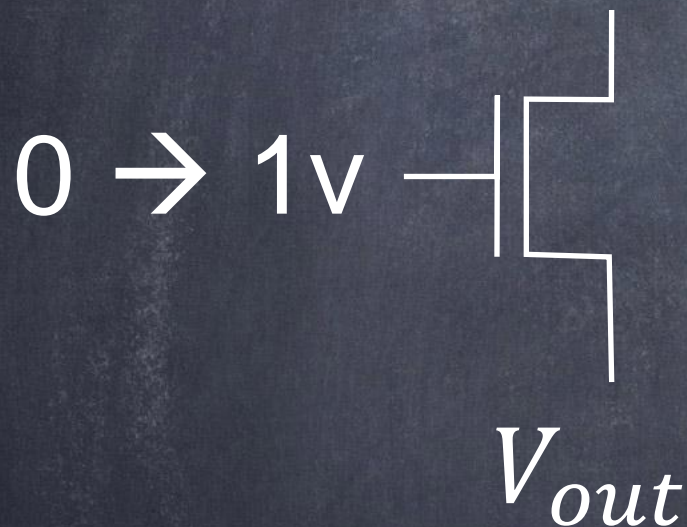




# NMOS as Pass transistor

$$V_t = 0.3 \text{ [V]}$$

1V



Conduction condition:

$$V_g - V_s > V_t$$

At  $t = 0^-$

$$V_{out} = 0 \text{ [V]}$$

$$V_g = 0 \text{ [V]}$$

$$V_g - V_s = 0 - 0 = 0 < V_t = 0.3 \text{ [V]}$$

$\Rightarrow$  No conduction

At  $t = 0^+$

$$V_{out} = 0 \text{ [V]}$$

$$V_g = 1 \text{ [V]}$$

$$V_g - V_s = 1 - 0 = 1 > V_t = 0.3 \text{ [V]}$$

$\Rightarrow$  Transistor conducts ( $V_{out}$  rises)

Conduction stops at

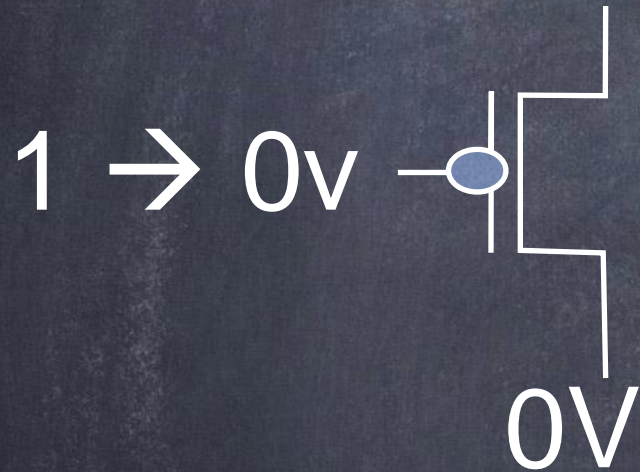
$$V_g - V_s = V_t \Leftrightarrow V_s = V_g - V_t = 1 - 0.3 = 0.7 \text{ [V]}$$



# PMOS as Pass transistor

$$V_t = -0.3 \text{ [V]}$$

$V_{out}$



Conduction condition:

$$V_g - V_s < V_t$$

At  $t = 0^-$

$$V_{out} = 1 \text{ [V]}$$

$$V_g = 1 \text{ [V]}$$

$$V_g - V_s = 1 - 1 = 0 > V_t = -0.3 \text{ [V]}$$

$\Rightarrow$  No conduction

At  $t = 0^+$

$$V_{out} = 1 \text{ [V]}$$

$$V_g = 0 \text{ [V]}$$

$$V_g - V_s = 0 - 1 = -1 < V_t = -0.3 \text{ [V]}$$

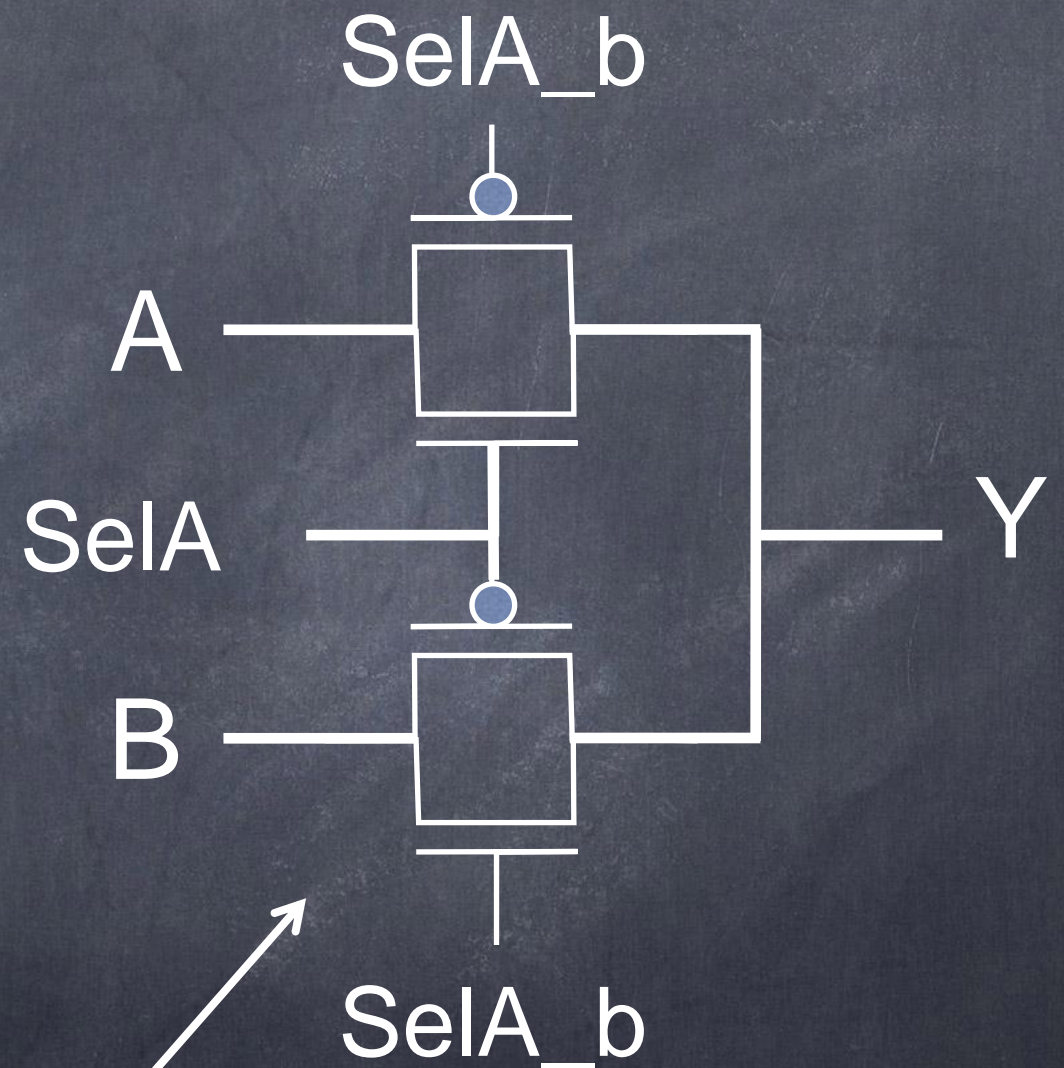
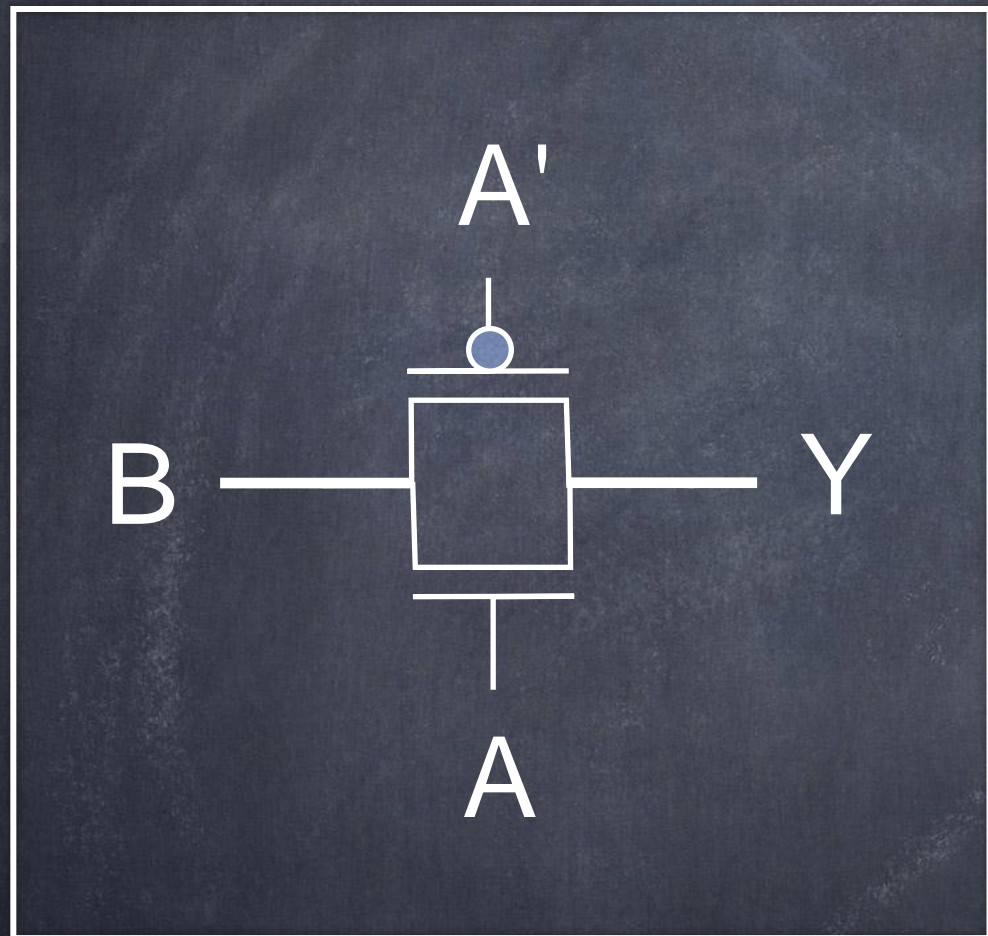
$\Rightarrow$  Transistor conducts ( $V_{out}$  decreases)

Conduction stops at

$$\begin{aligned} V_g - V_s = V_t &\Leftrightarrow V_s = V_g - V_t = 0 - (-0.3) \\ &= 0.3 \text{ [V]} \end{aligned}$$



# Pass Gate

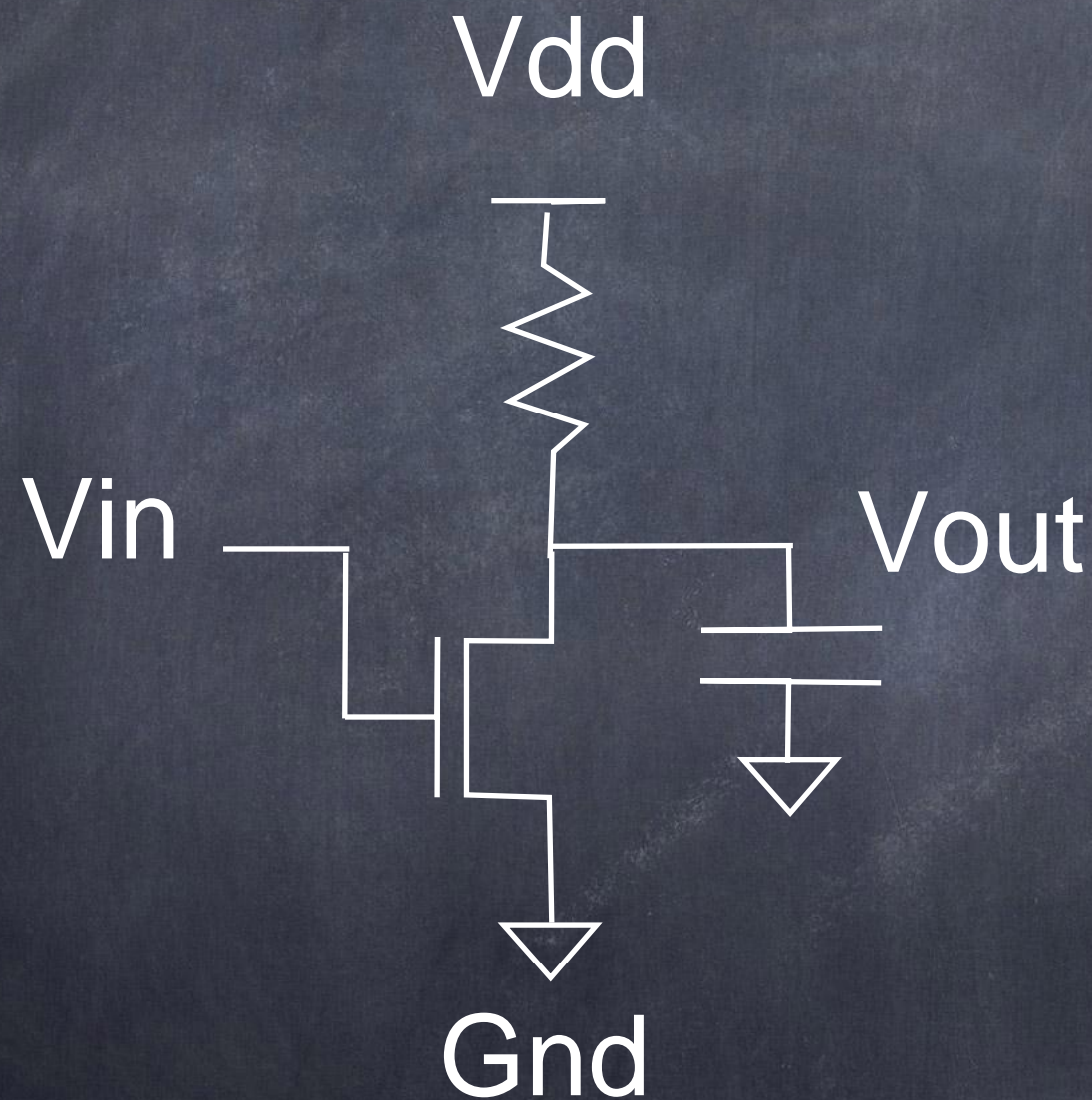


Is this a good digital circuit?  
- Still it could be handy





# NMOS logic



What is the value of  $V_{out}$  when  $V_{in} = V_{dd}$  ?

When current will stop flowing?

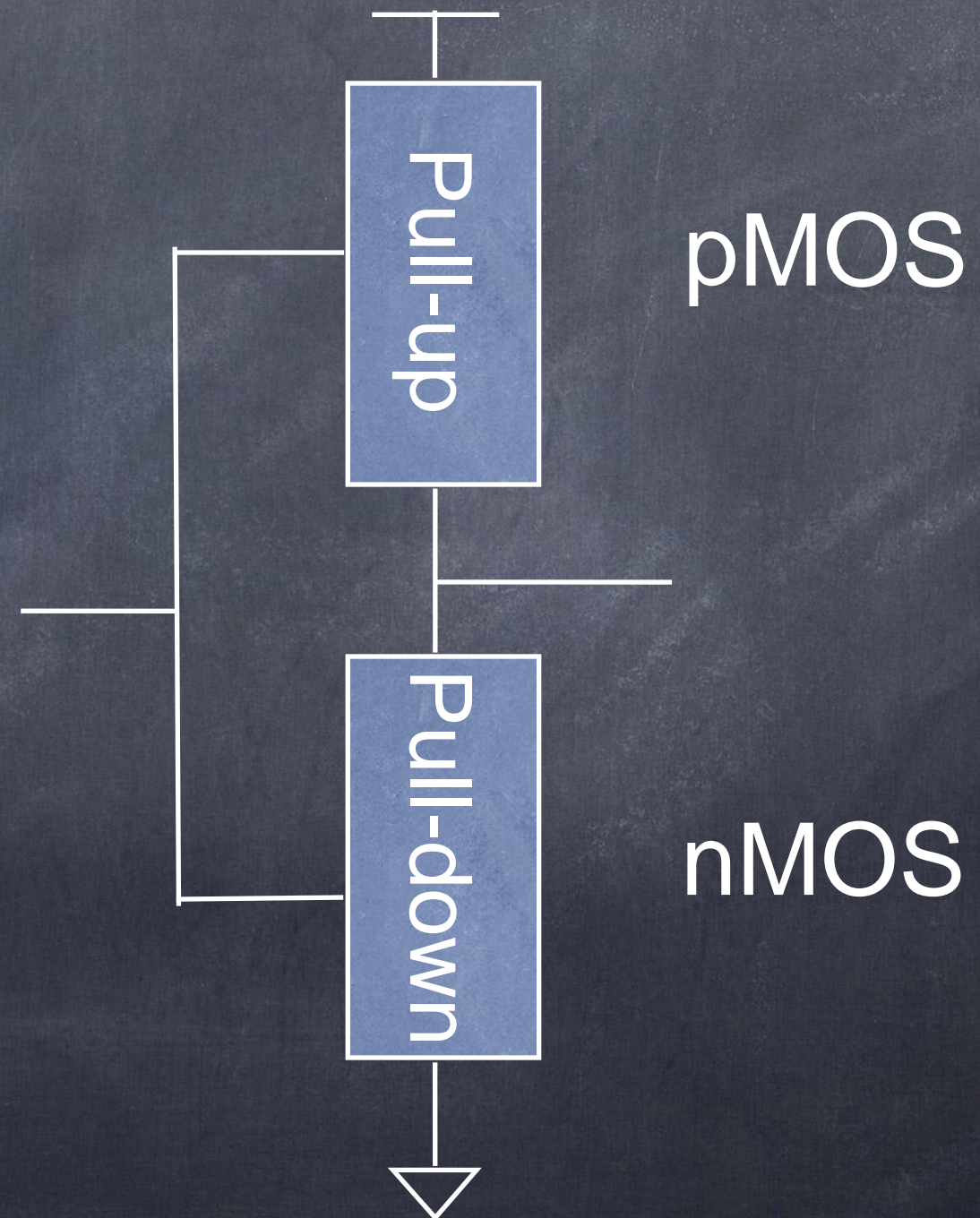
Which states dissipate energy?



# CMOS Gates

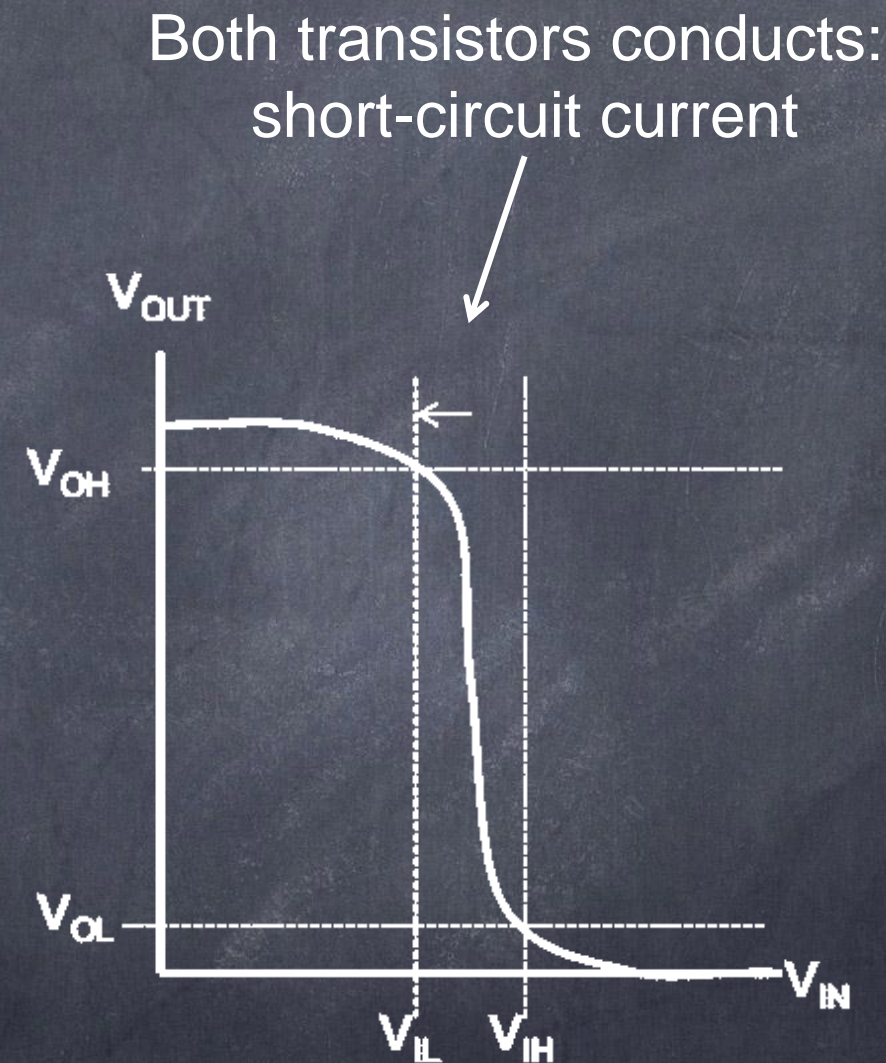
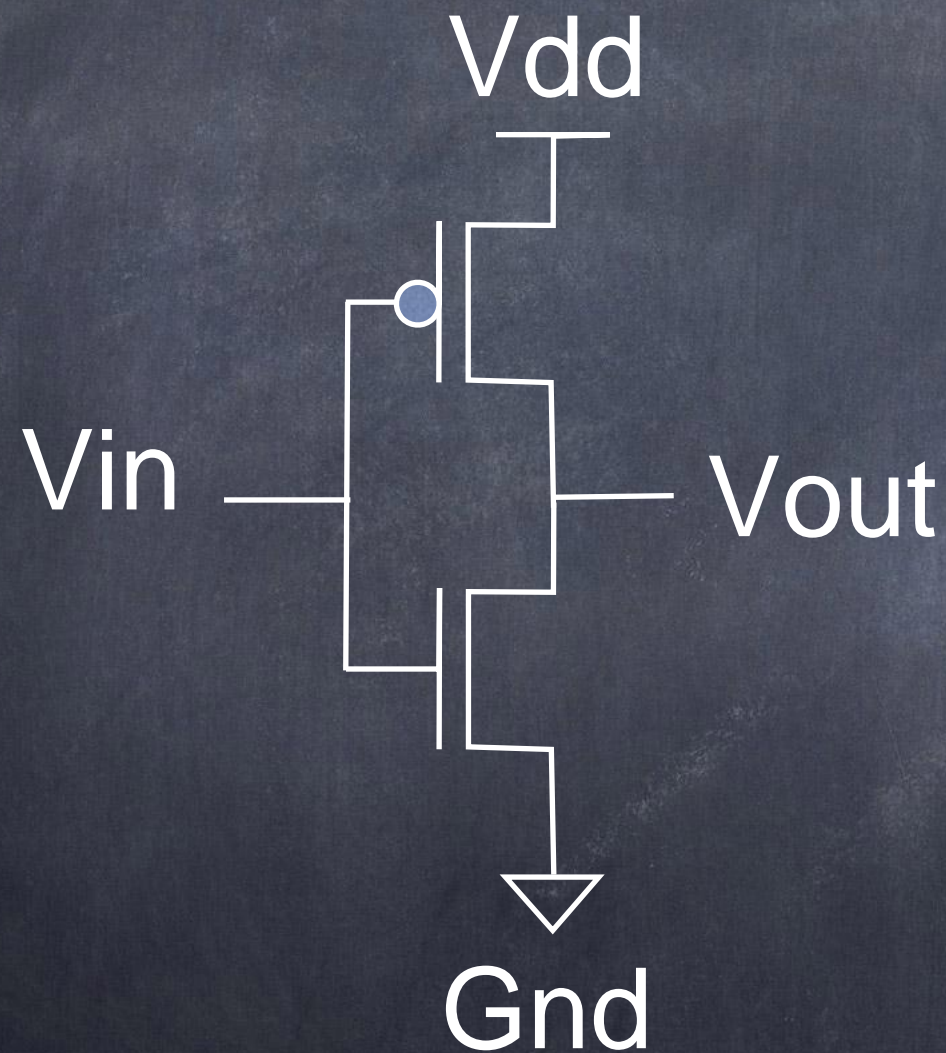
## Pull-up / Pull-down networks

- CMOS: Complementary MOS
- No floating wires, outputs connects to either Vdd or Gnd.
- Vdd & Gnd are never shorted together.





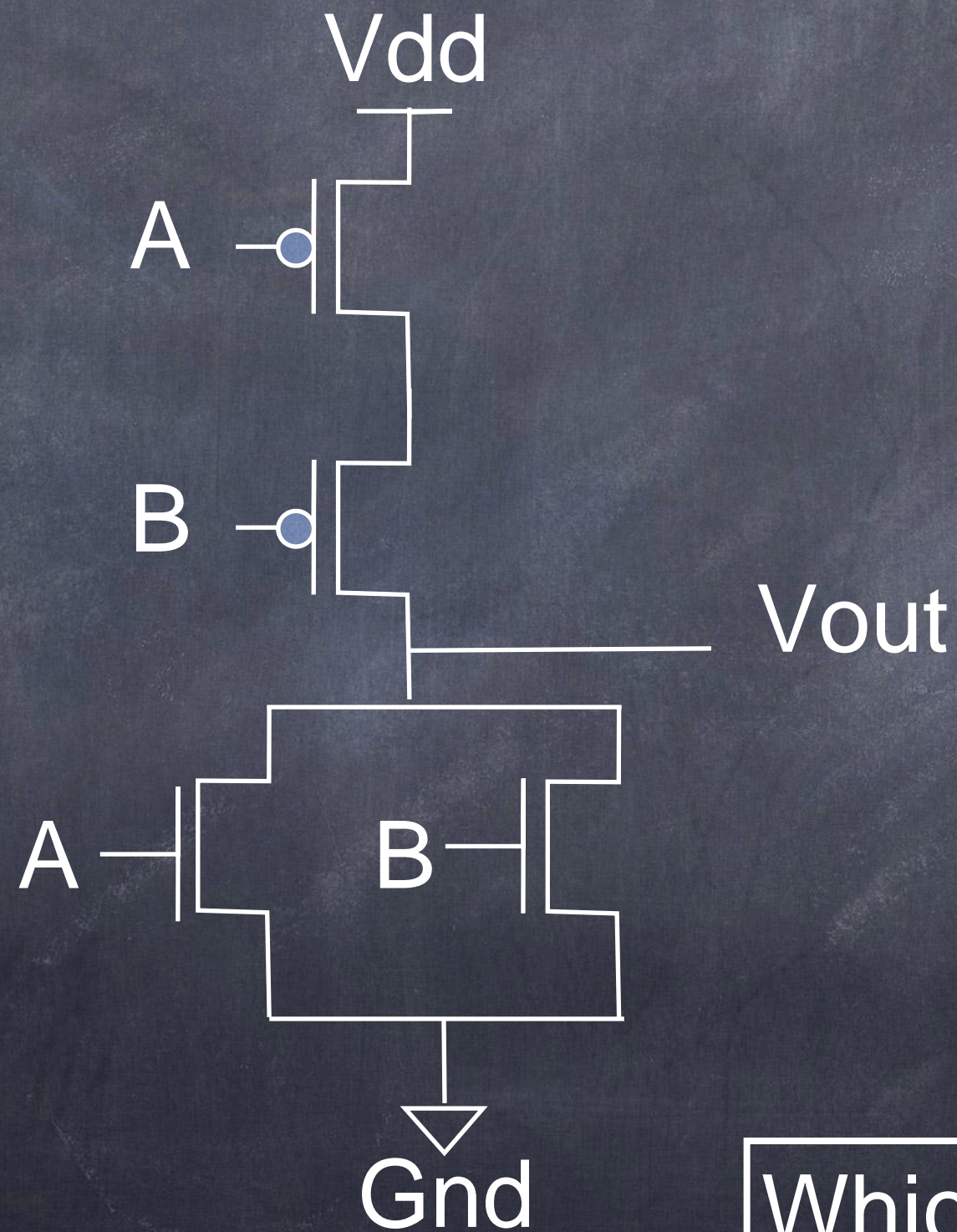
# The Inverter



Identify regions? Which MOS, Which region?



# More Gates



Which gate is this?



# More Gates

NOR gate:

- OR branch discharges to ground (logic 0)
- Dual branch charges to Vdd (logic 1)

Dual:

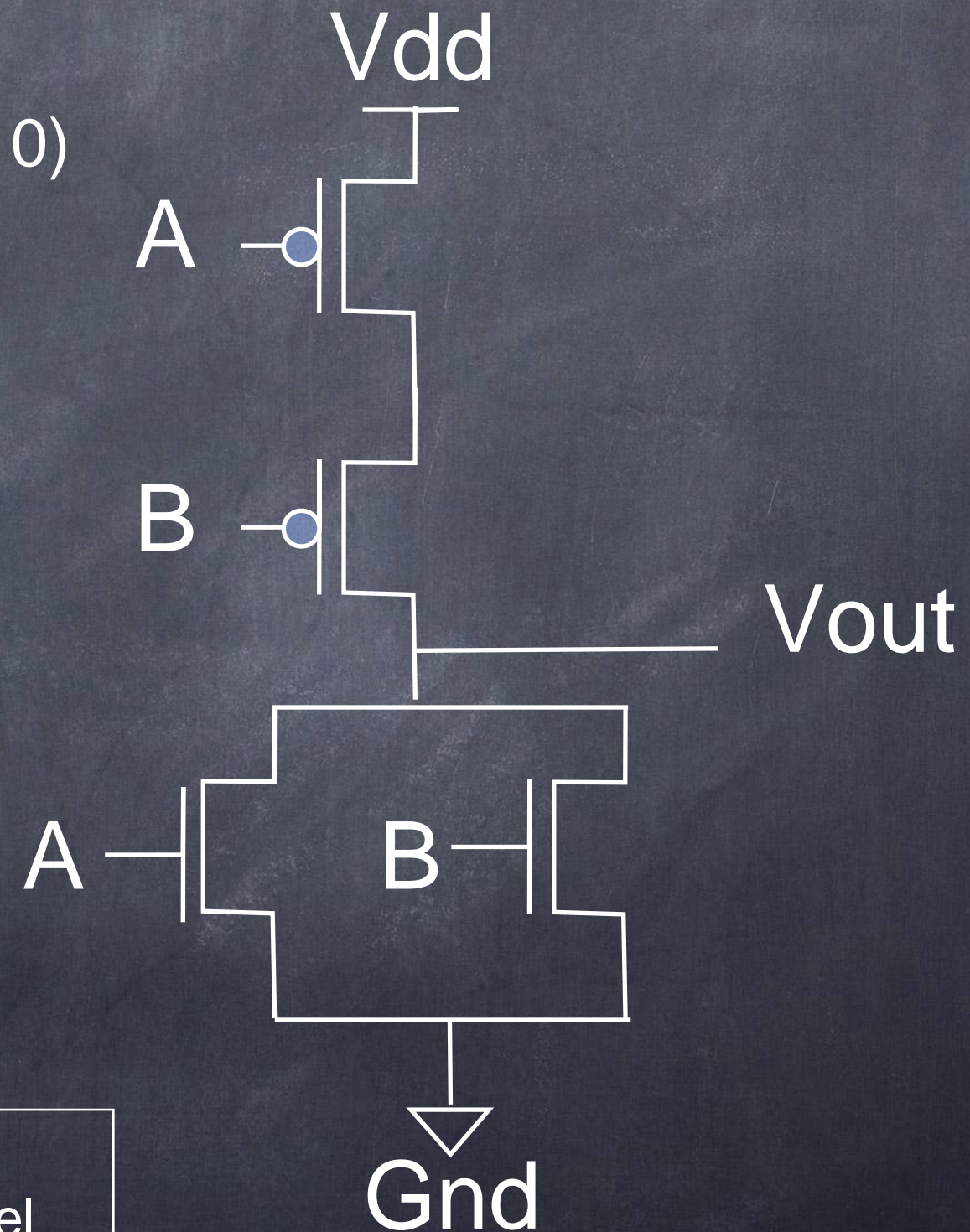
- The complementary branch can be obtained from De Morgan's law

$$(A+B)' = A' * B'$$

$$(A*B)' = A' + B'$$

Note that:

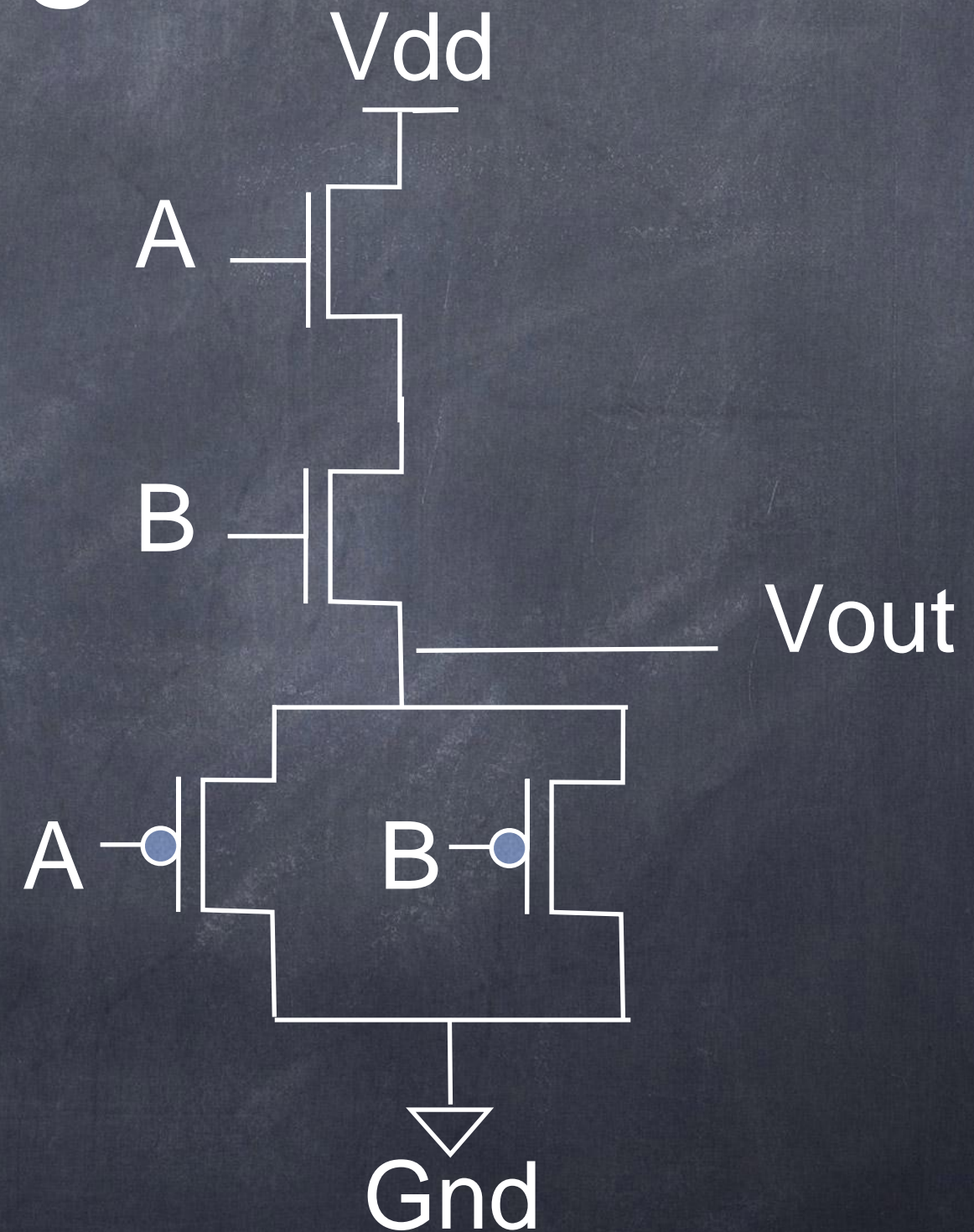
OR operations are implemented by switches in parallel  
AND operations are implemented by switches in series





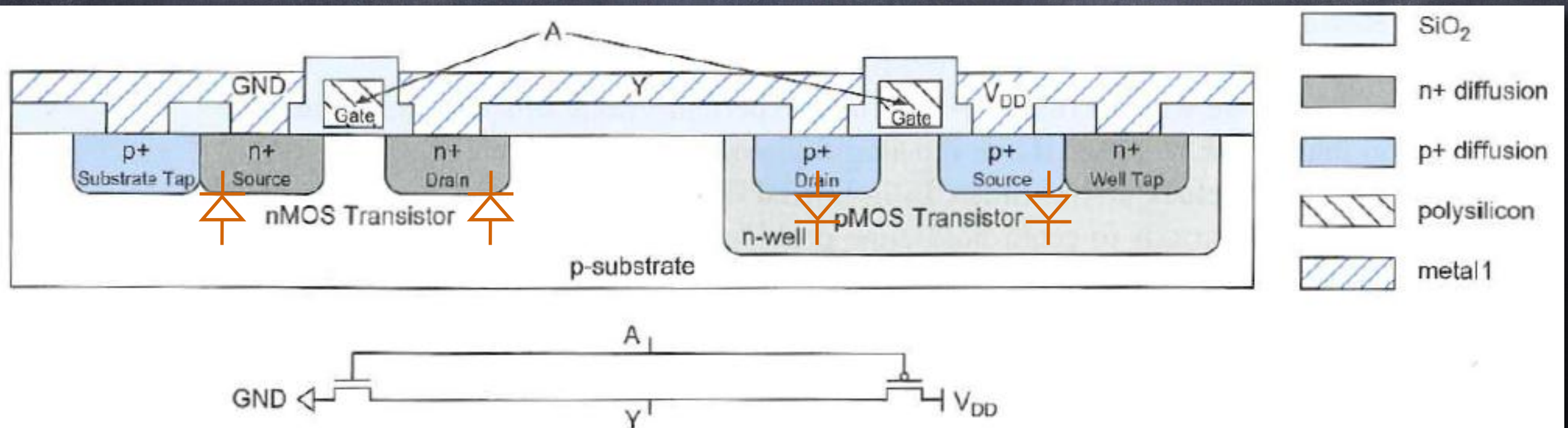
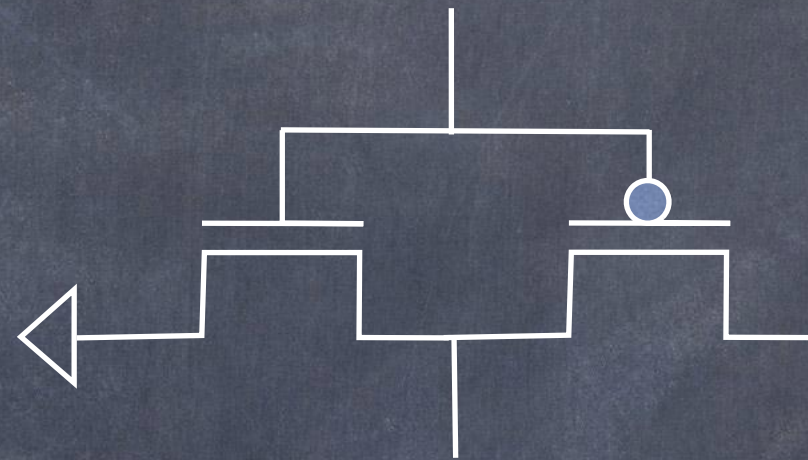
# Direct Logic?

- What is the problem with this gate?





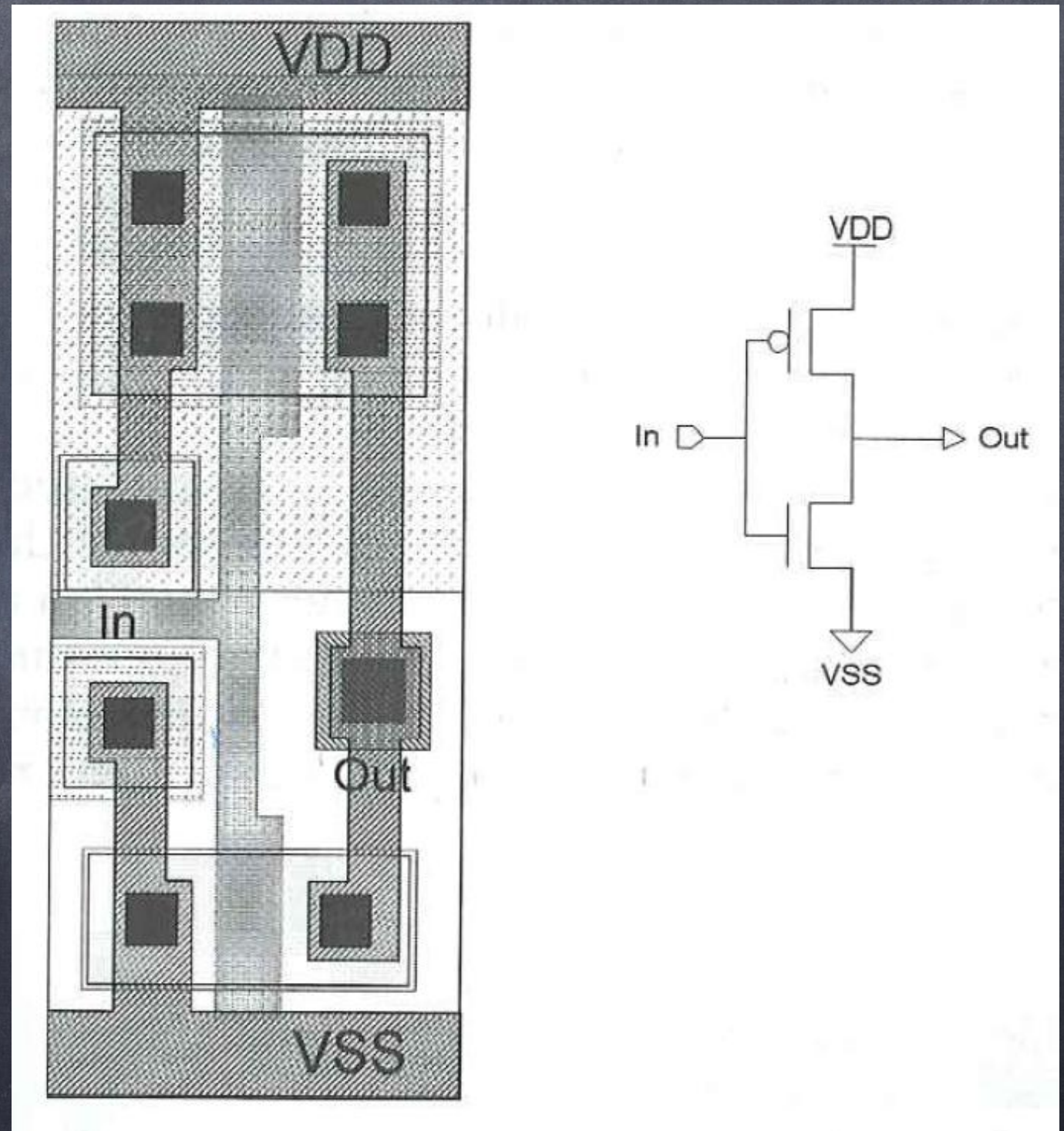
# Gate Layout





# Standard Cell

- A contained circuit that can be handled by tools.
- It has a standard height which ease placement on the chip area
- Associated with model that characterizes its physical and logical properties.

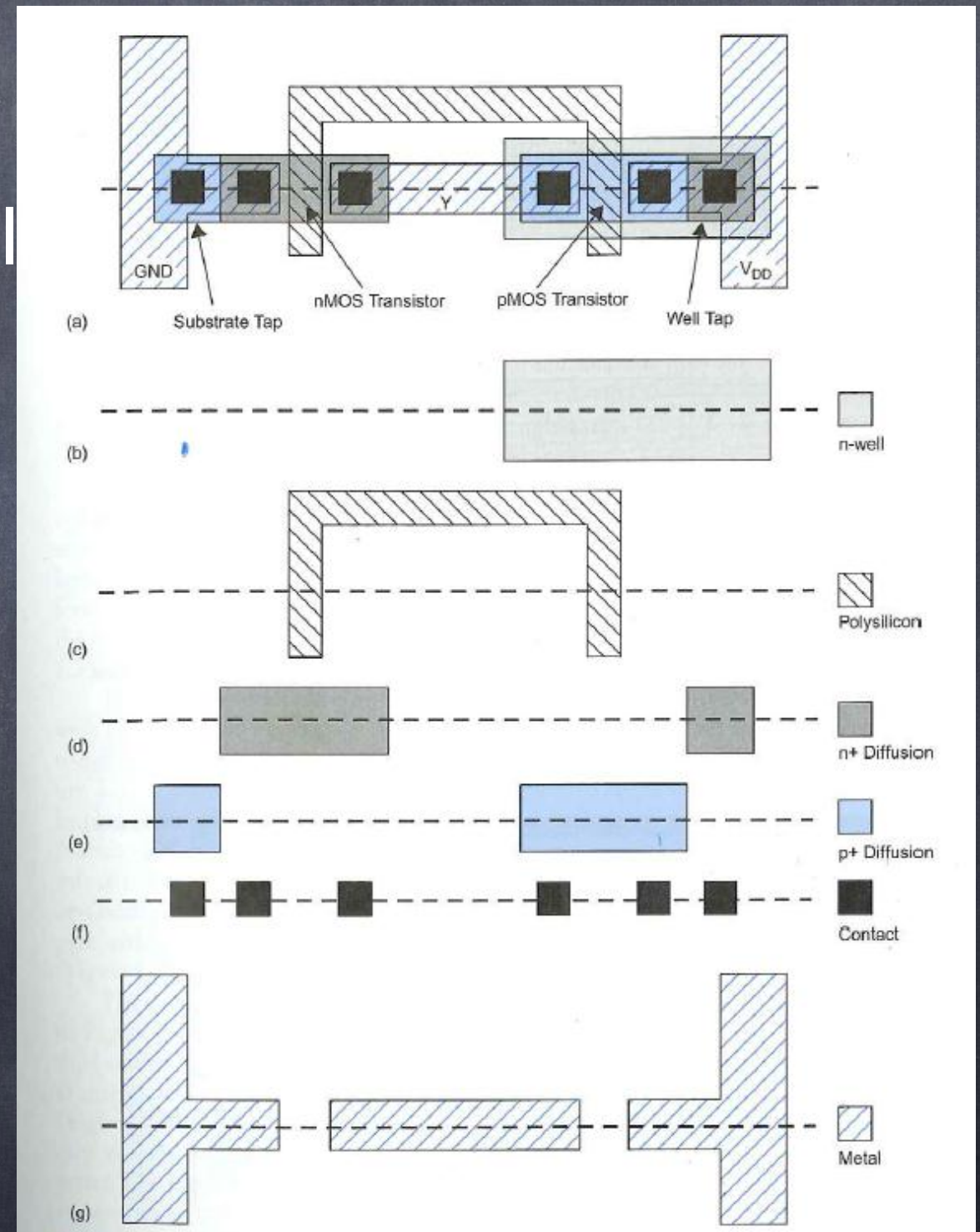




# Gate Layout (Standard Cell)

- We need to communicate a design intent without handling all fabrication details.
- Draw layers, simple forms that contain the information required to build our circuits.
- Foundry provides Design Rules (DRC) to guarantee that what's delivered is feasible to build.

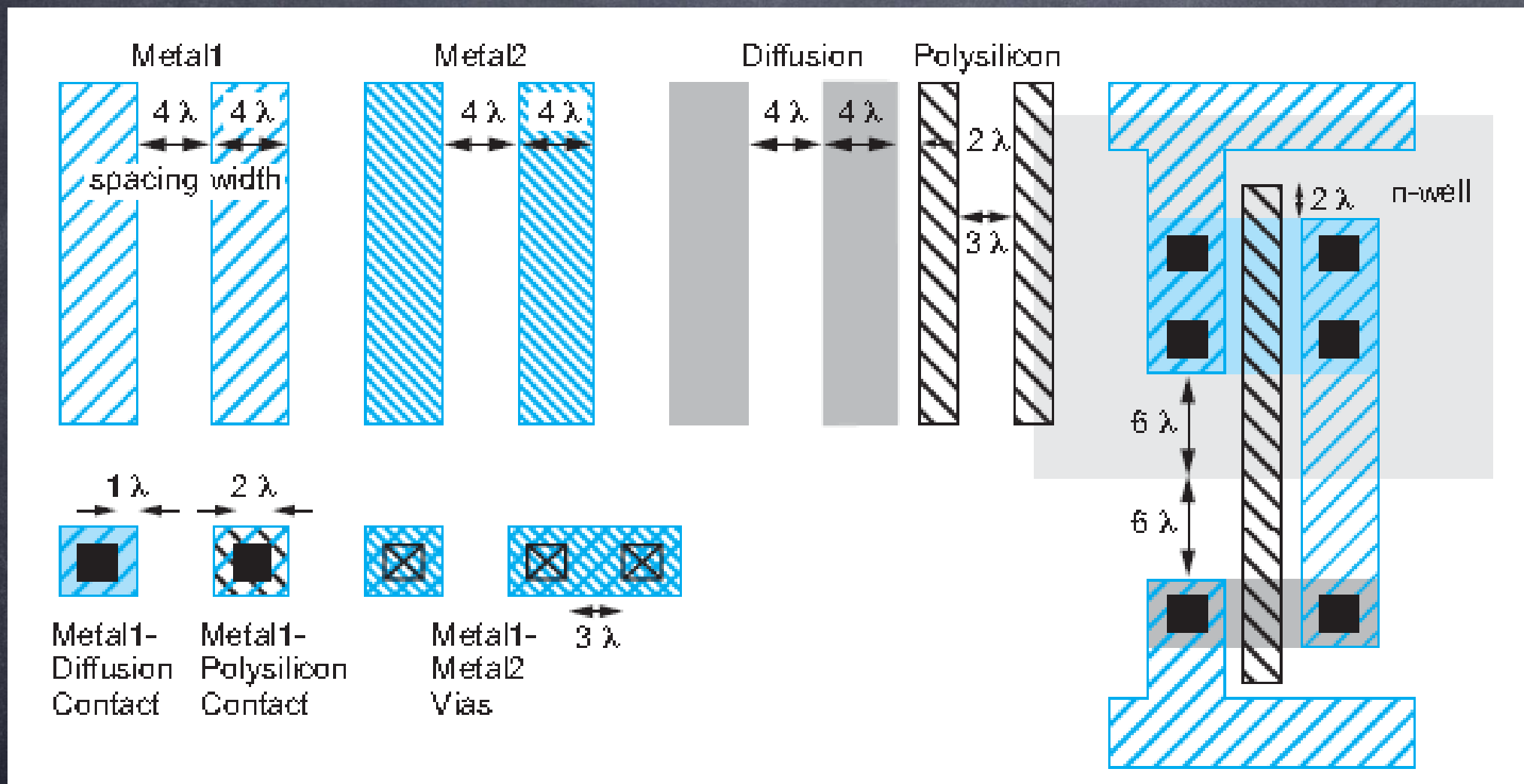
<http://www.mosis.com/files/scmos/scmos.pdf>



*\*Weste, Harris - CMOS VLSI Design 4th Edition*



# Rules



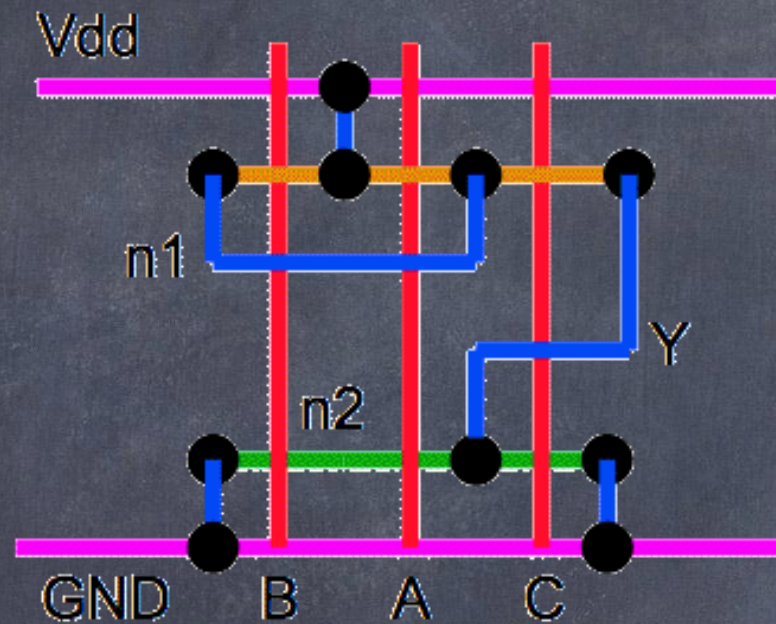
## Rules for MOSIS process

Note that they are based on a single parameter

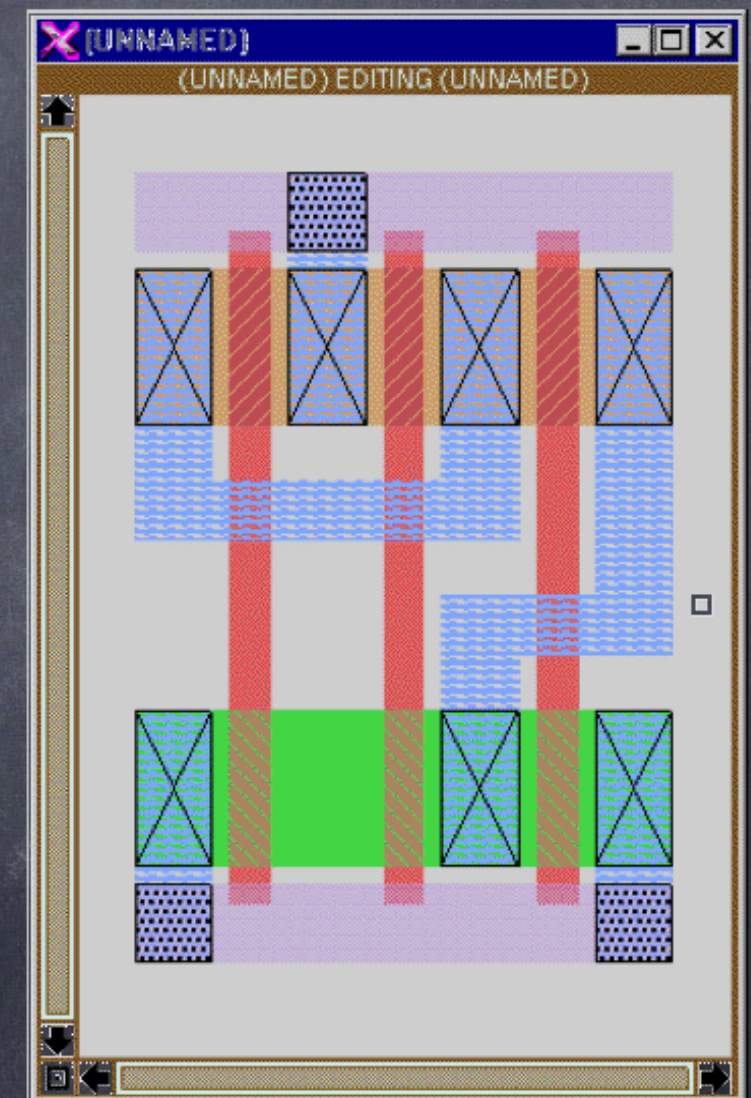
$\lambda$  represents half of the minimum transistor channel length  
(or in other words, half of minimum polysilicon wire width)



# Stick Diagrams (MacGyver's clip)

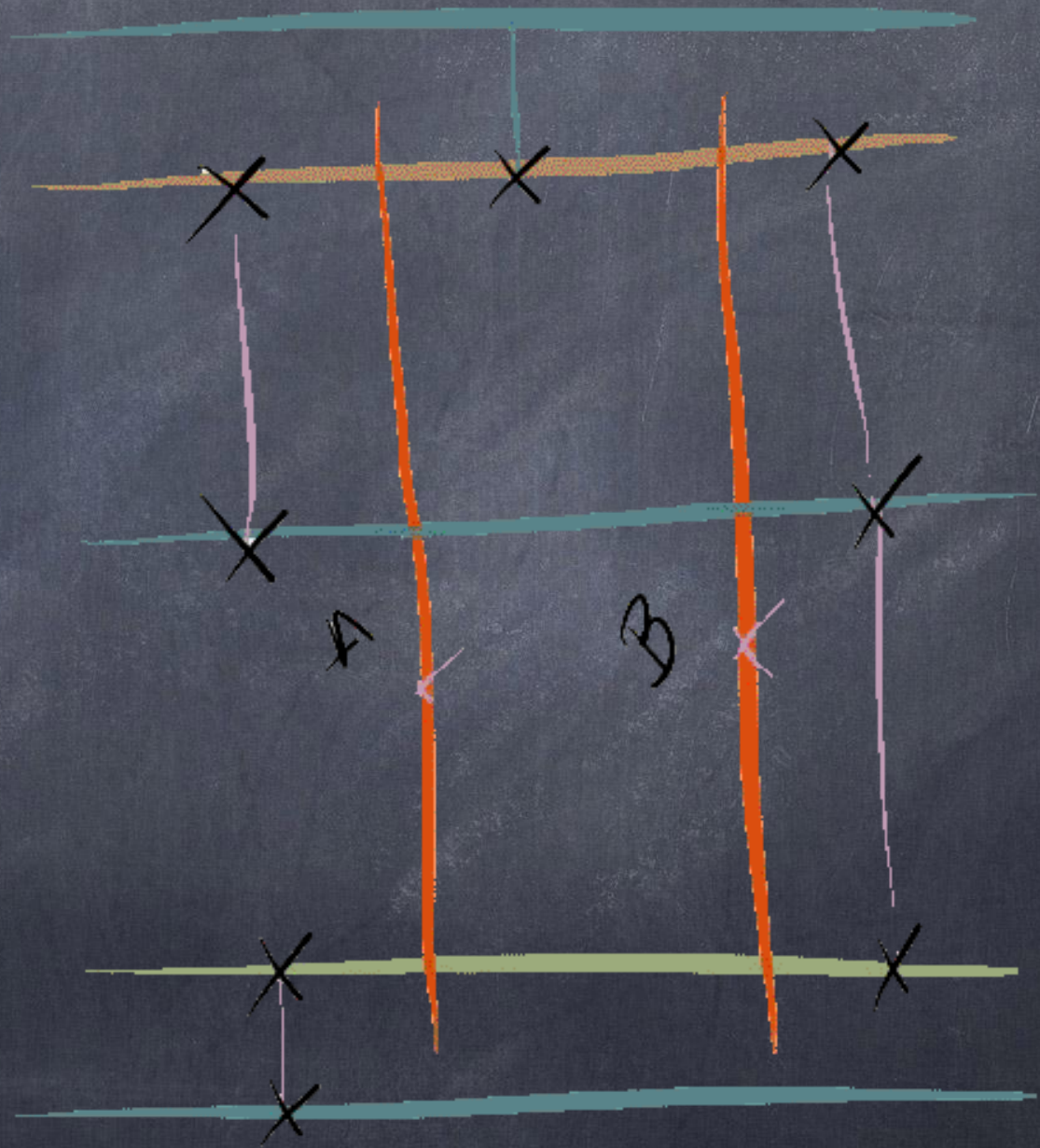
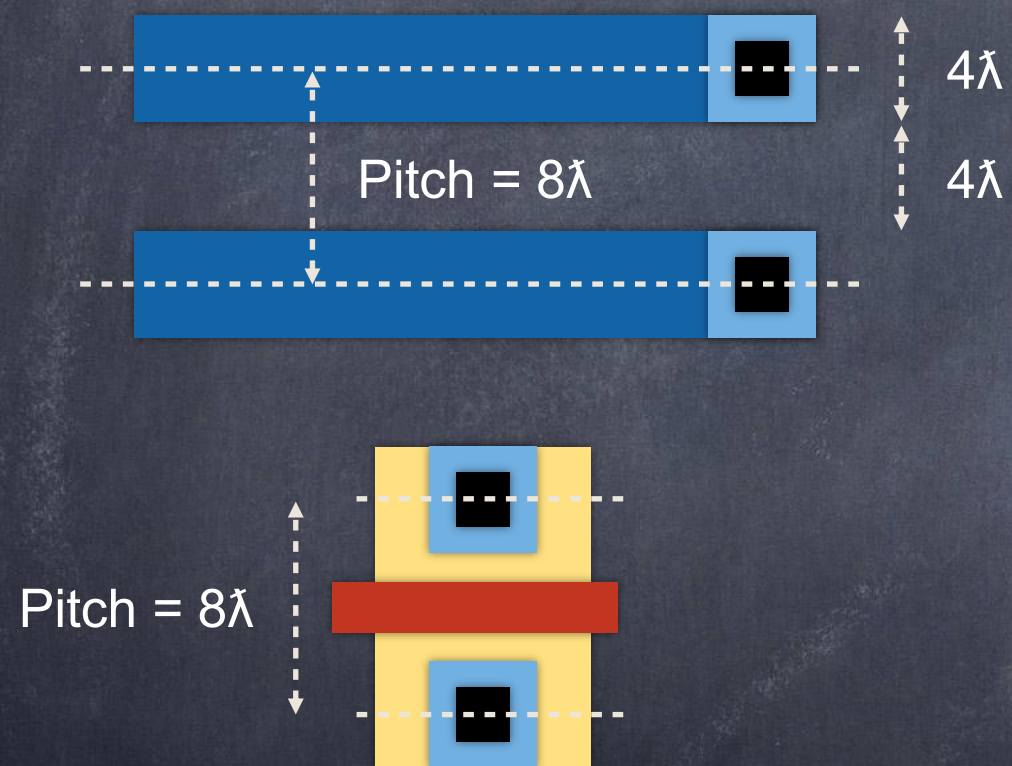


- Abstract version of layout
- Workout topology without the details



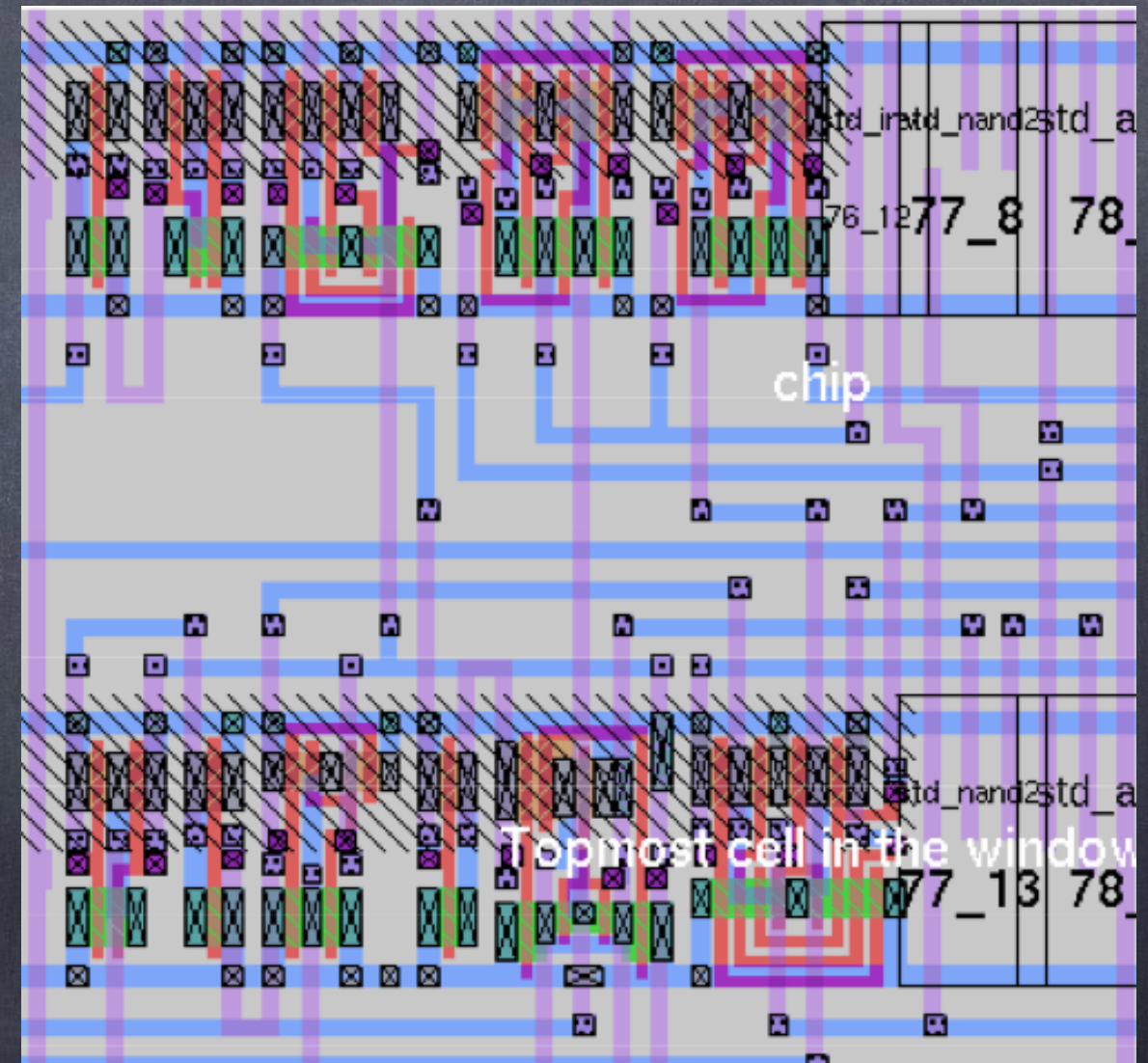
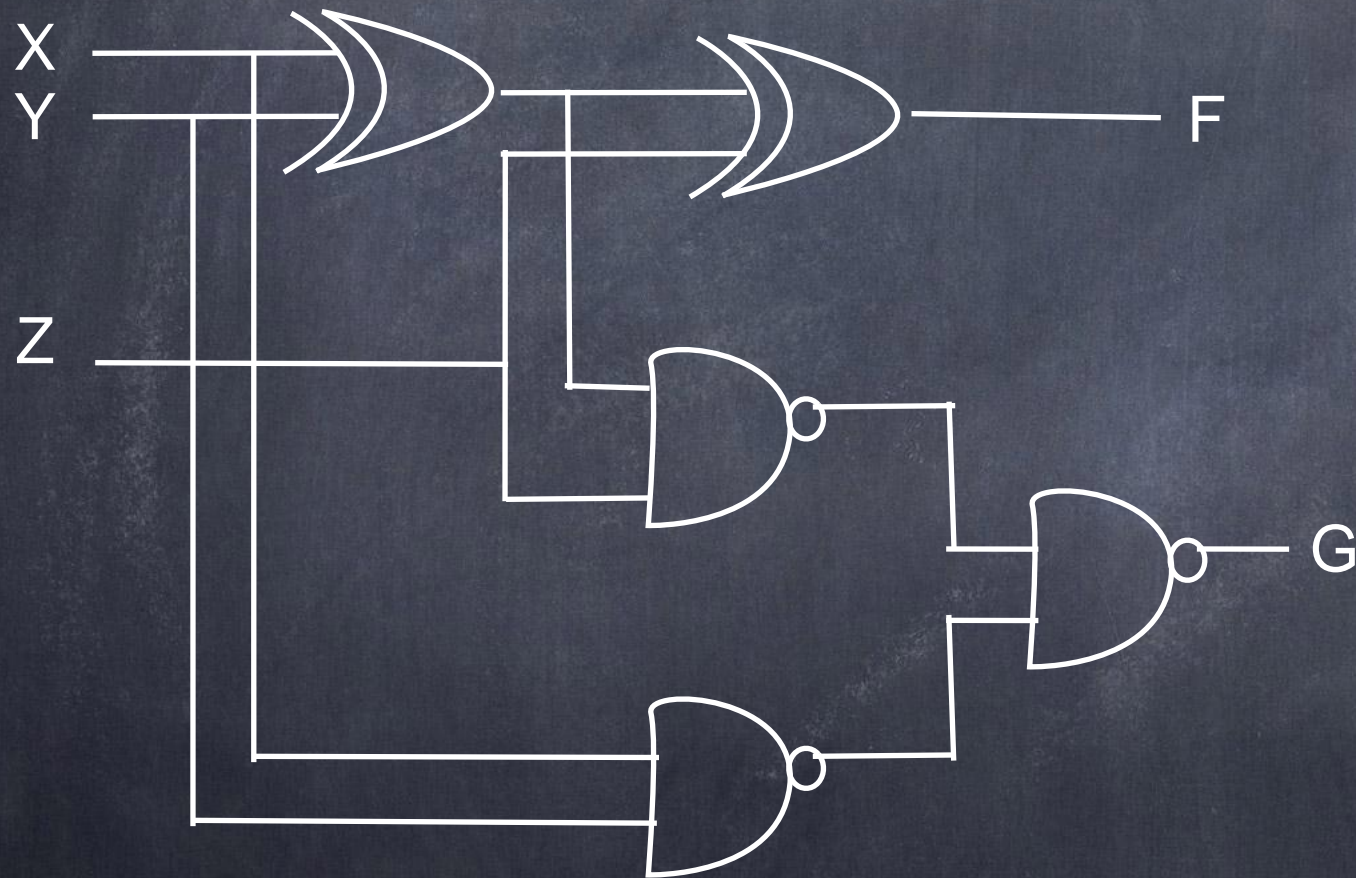


# Quick area estimation





# Place & Route





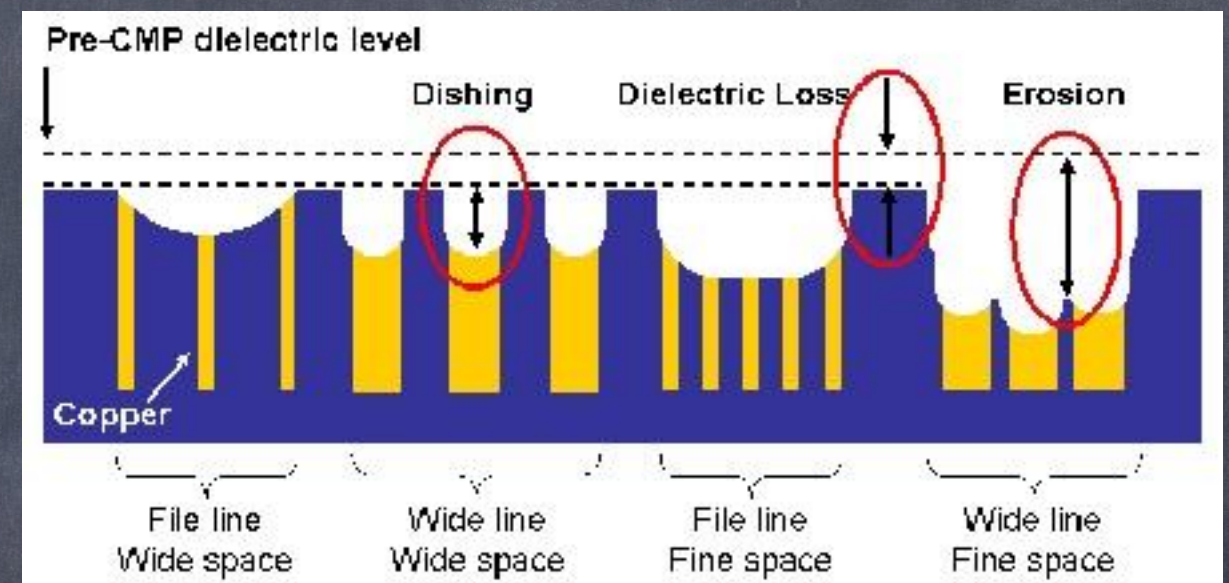
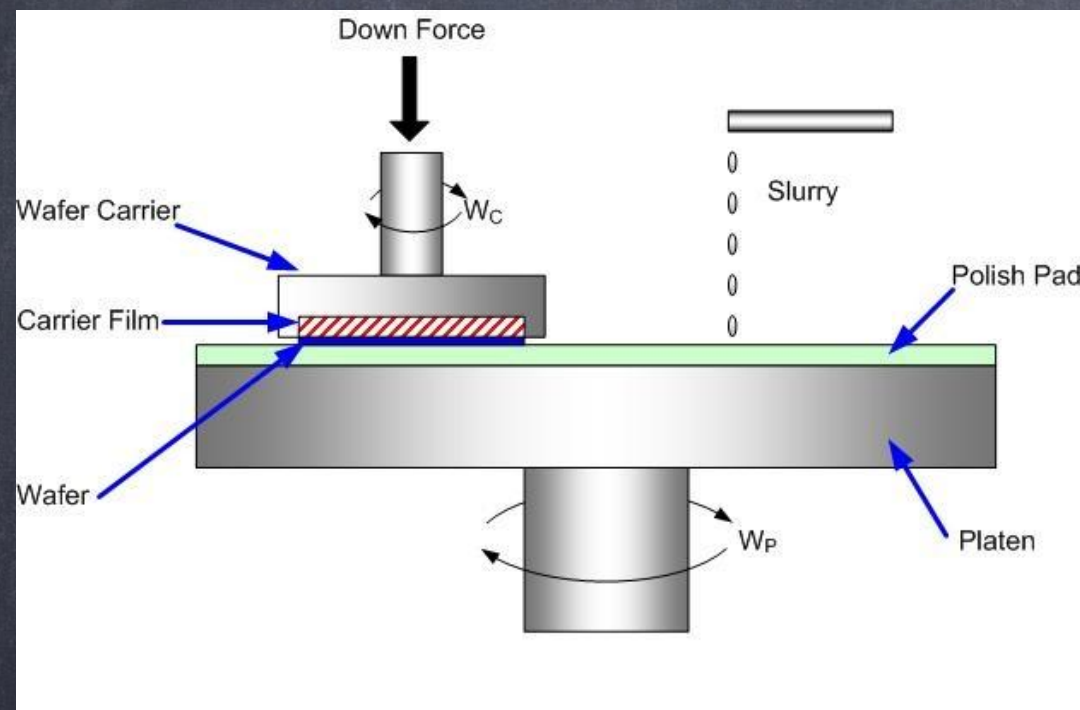
# More subtleties of Manufacture

- Metal density
- Metal Slotting
- Antenna Rules
- Optical proximity correction (<180nm)
- Phase shifting masks
- Double Patterning (<45nm)



# Metal Density

## Chemical Mechanical Polishing



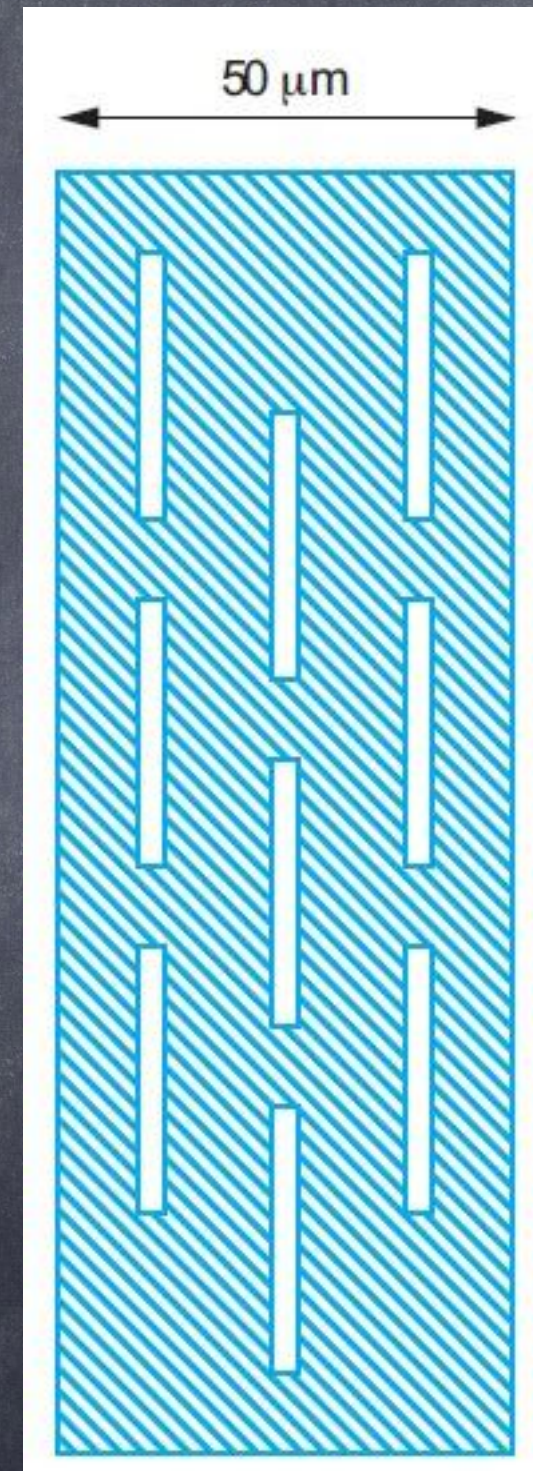
Copper is more sensitive to polishing

This can also be an issue during Etching.  
Bottom line: each layer has a density target (max & min)



# Metal Slotting

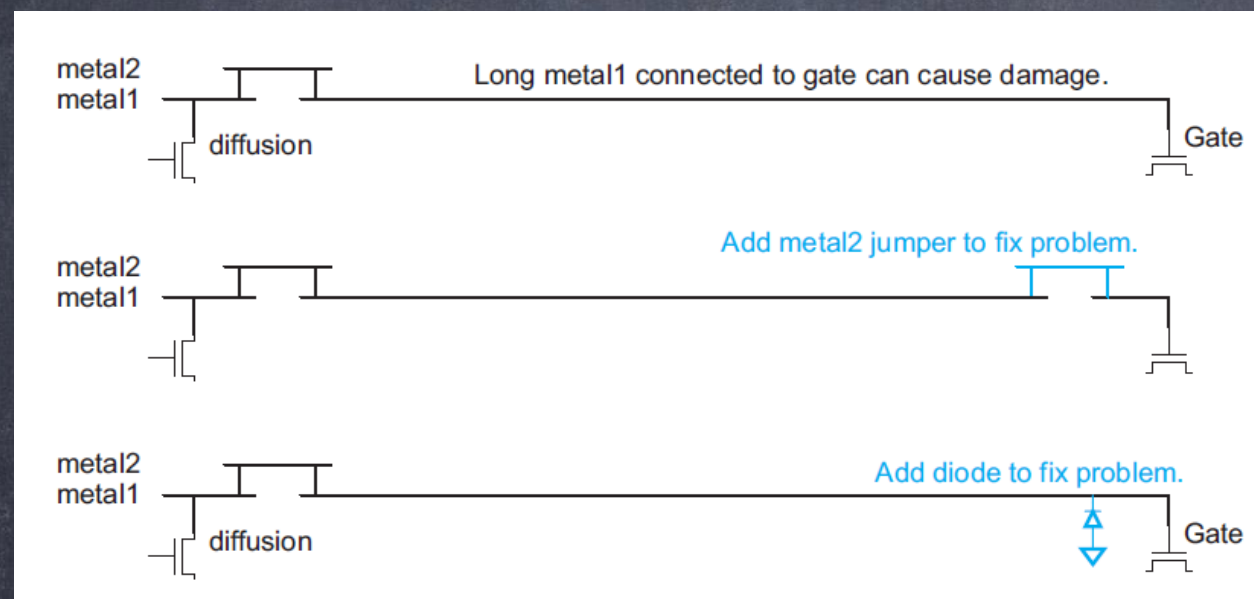
In some process, slots should be introduced for wide wires in order to relieve stress and reduce risk of electromigration





# Process-Induced Damage

## Antenna Rules

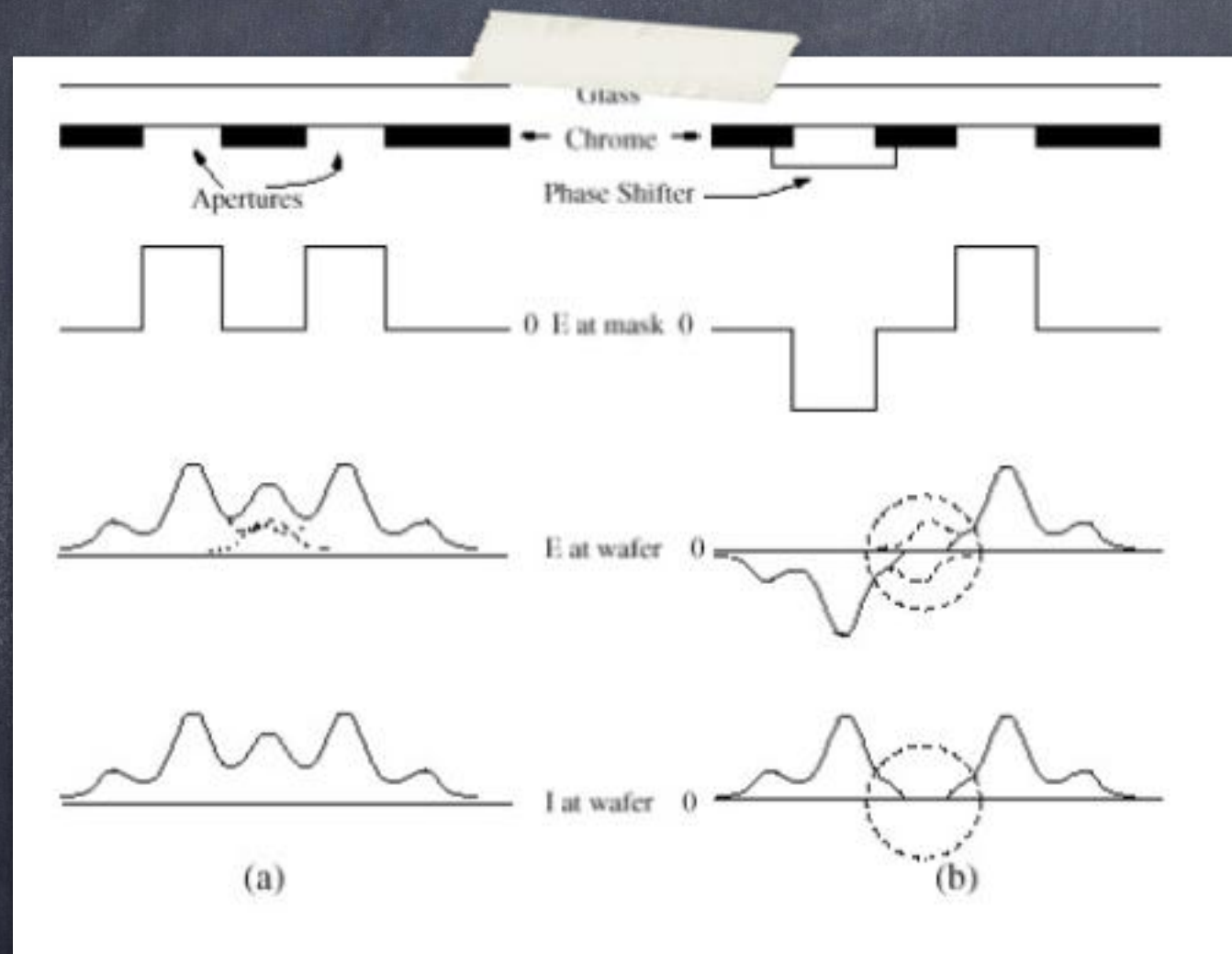


$$\text{Target} = \frac{\text{Area Metal}}{\text{Area Gate}}$$

Wire is charged during etching and can gather enough voltage to damage transistor gate



# Phase Shifting Masks (PSM)

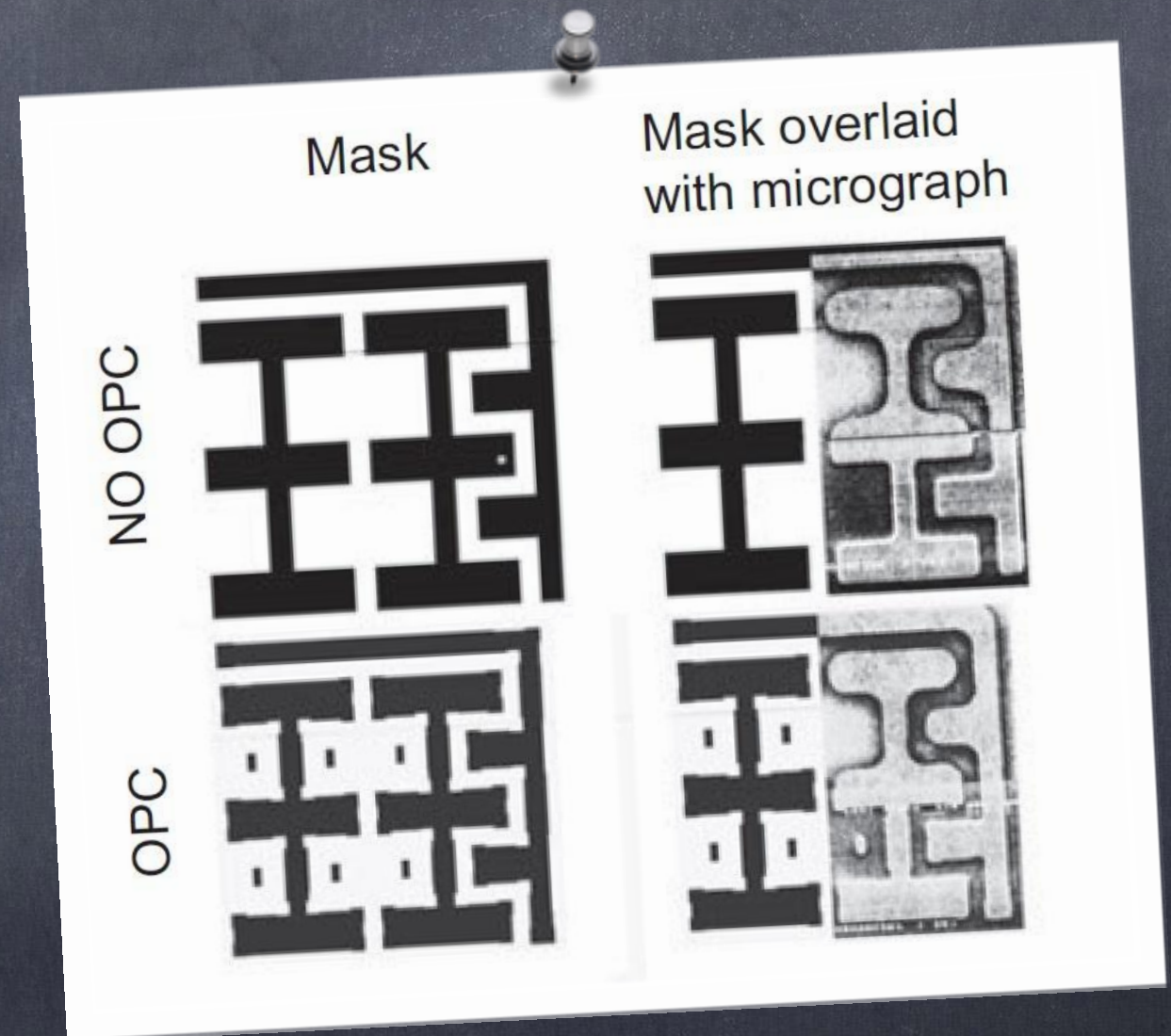
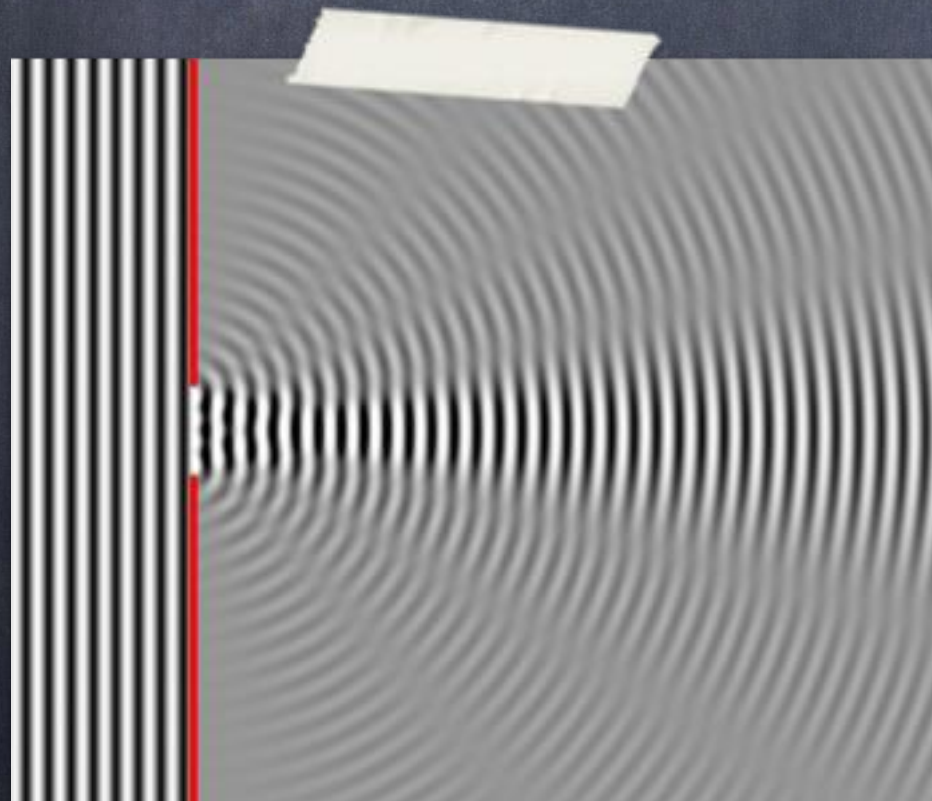


Adjacent Transparent parts are made with opposite phase so that the intersections can be subtracted, thus increasing resolution.



# Optical Proximity Correction (OPC)

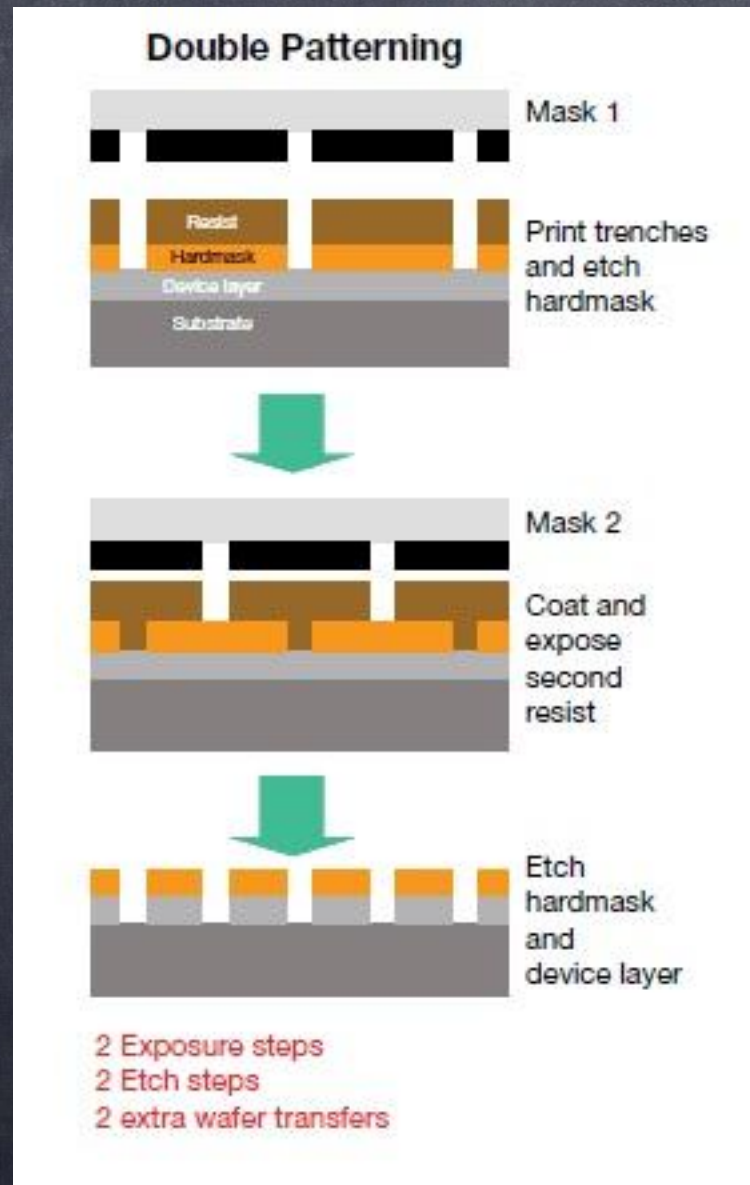
Non-Uniform exposure\* is compensated in the mask



\*Center receive more light than edge due to diffraction



# Double Patterning



Use two precisely aligned mask and two exposure steps to reduce pitch

\*Future Fab Intl. Issue 28. Michael Lercel, IBM



# Quiz for Understanding



# Draw the circuits for the functions below

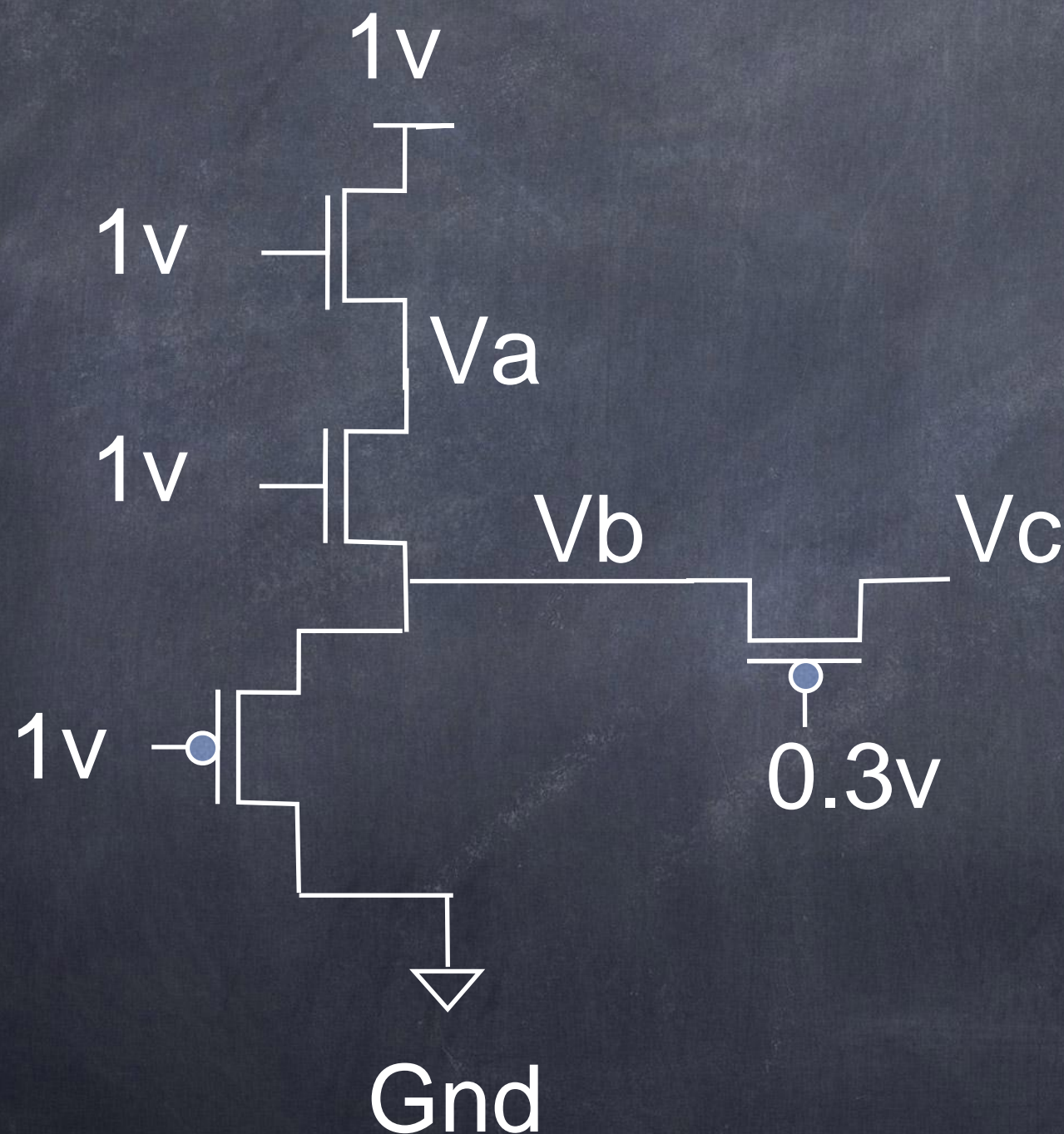
- $A+B$
- $(A*(B+C))'$
- $A \text{ xor } B$



# Calculate Node Voltages

Assume that at  $t = 0$ ,  
all nodes are at 0 [V]

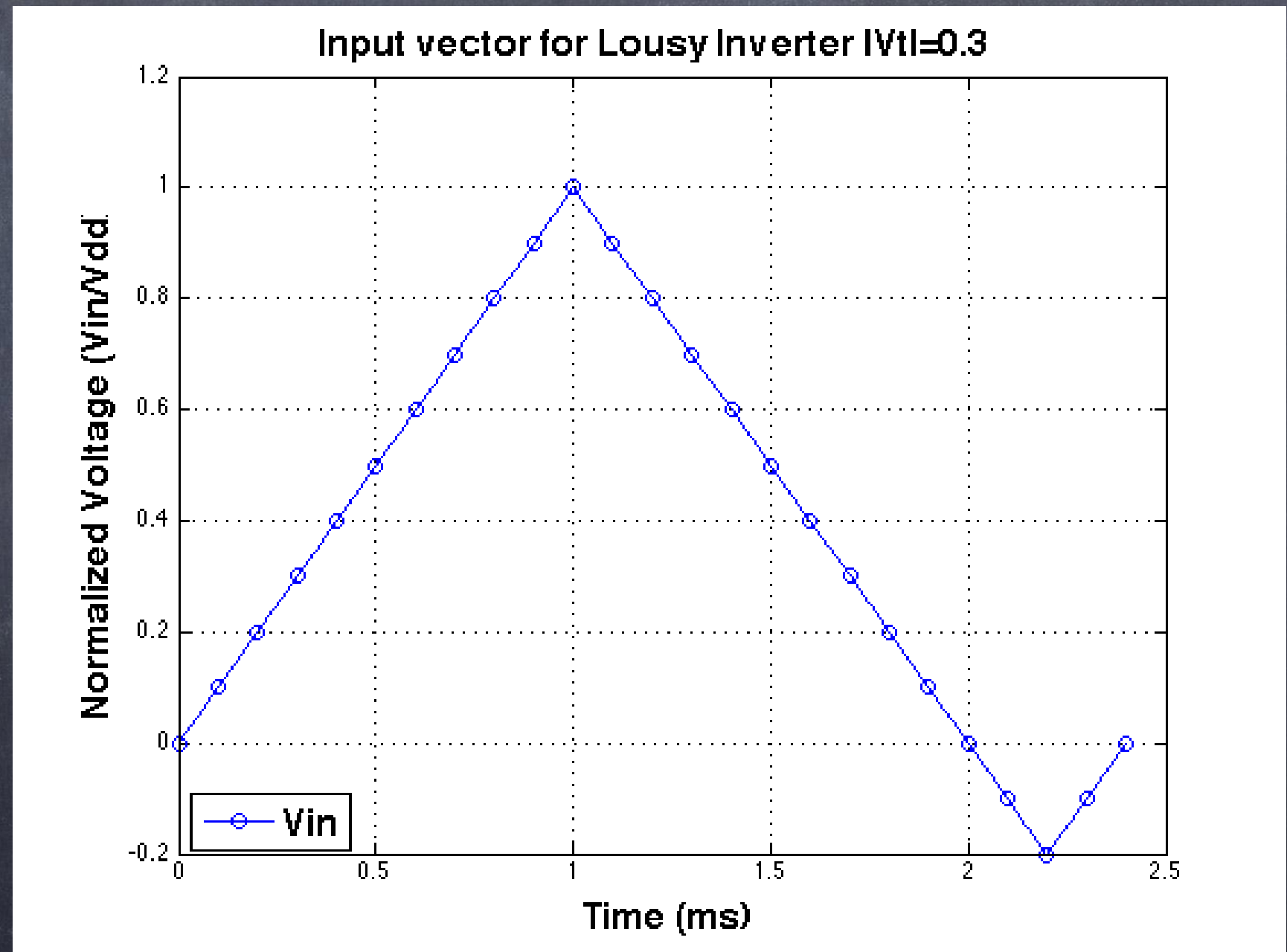
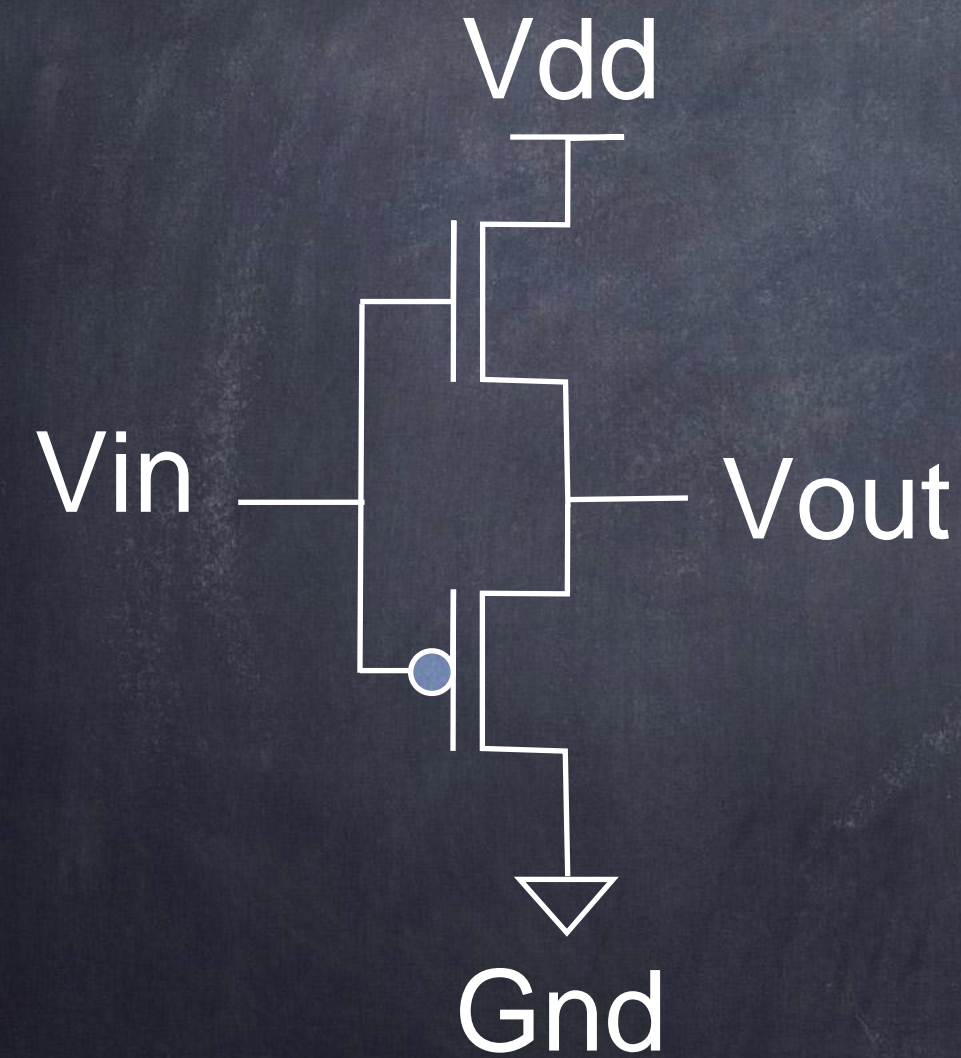
$|V_t| = 0.3$



Node	Voltage
$V_a$	
$V_b$	
$V_c$	



# Plot the output response for the given input





# Summary

- Silicon technology enables cheap and efficient computation
- Good CMOS gates are:
  - Uni-directional
  - Rail to rail
  - Noise attenuated
  - Defined by binary equations
  - Low dynamic power dissipation
- Standard Cells
  - Allows tools to handle circuits, synthesis / place & route



# References

- *Weste, Harris - CMOS VLSI Design 4th Edition*
- *Rabaey, Digital Integrated Circuits*
- *Moore65, "Cramming more components onto integrated circuits"*
- *Dennard74, "Design of Ion-Implanted MOSFET's with Very Small P"*